

Radiation Mitigation Techniques ***(for Mixed-Signal Circuits)***

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Hardening Techniques for AMS Circuits



- Radiation Effects in AMS Circuits: Unique issues and considerations
- Total Ionizing Dose and Basic Mitigation Strategies
- Single Event Effects and Basic Mitigation Strategies
- Hardening by Design for AMS
- A look to the future
- Summary

Observation of Single Event Upsets in Analog Microcircuits

R. Koga, S.D. Pinkerton, S.C. Moss, D.C. Mayer, S. LaLumondiere,
S.J. Hansel, K.B. Crawford, and W.R. Crain

The Aerospace Corporation

PO Box 92957, Los Angeles, CA 90009

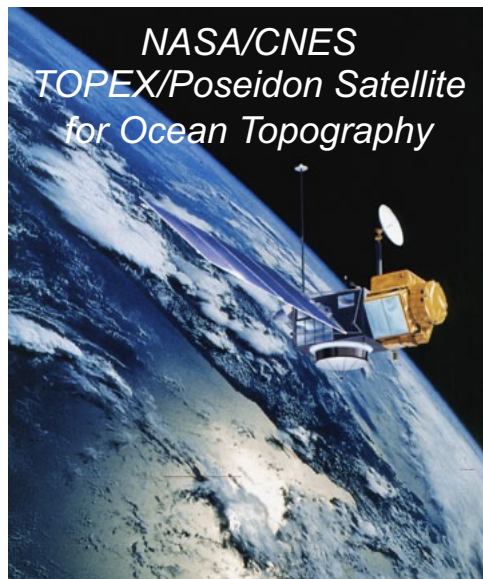
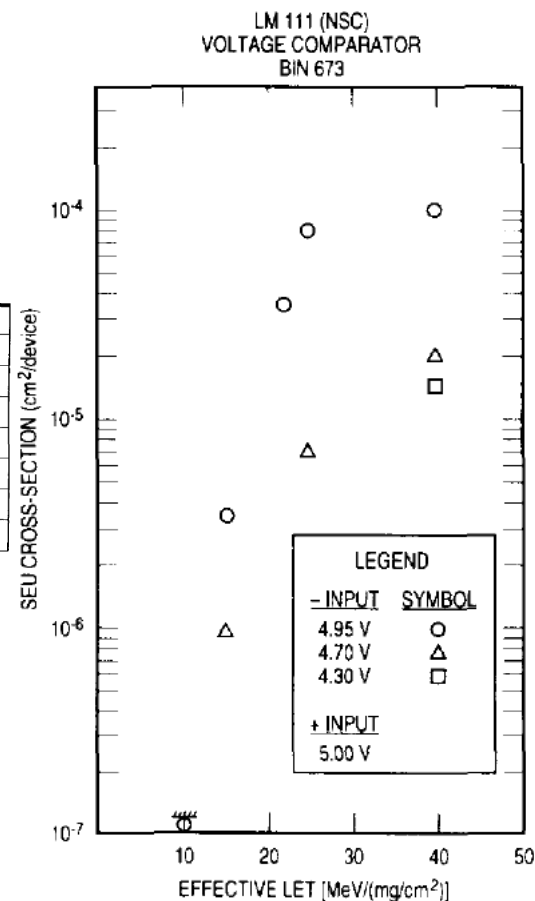
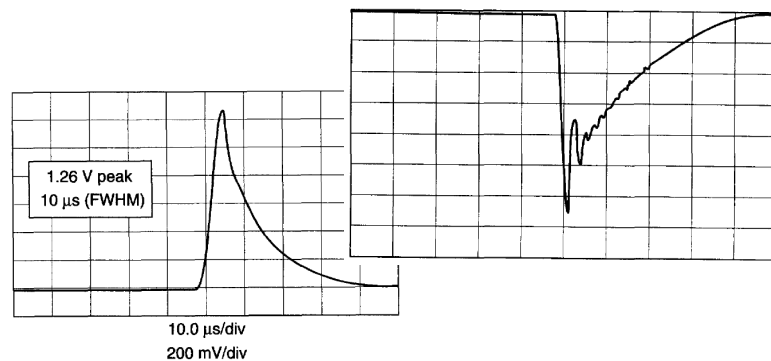


Image courtesy JPL/NASA



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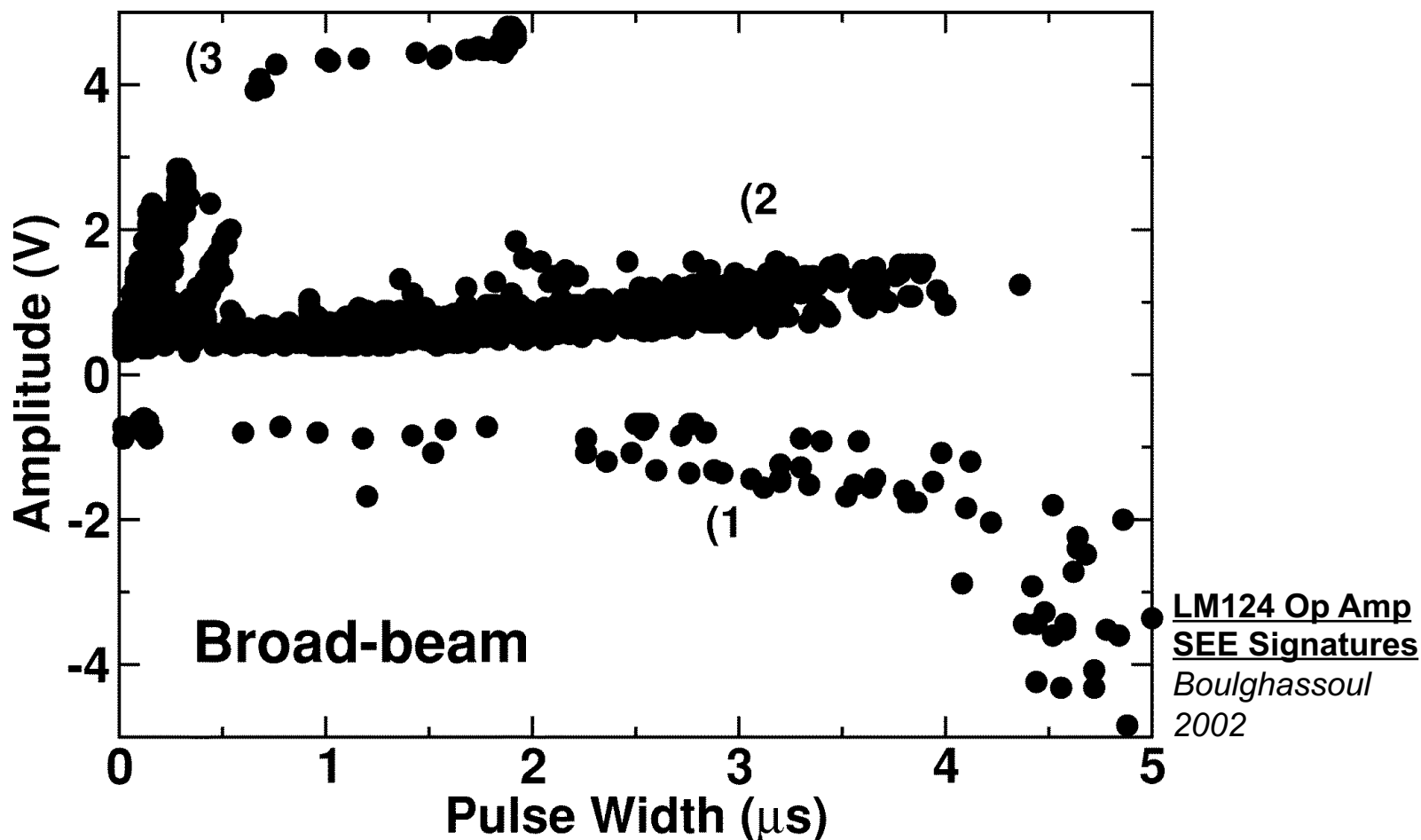
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- Suggested the first 2 “mixed-signal” strategies for mitigating single event effects (SEE) that have since become commonplace
 - **Temporal redundancy**: It was suggested that multiple consecutive samples could be taken at the analog-to-digital interfaces (thresholds)
 - **Increase design margins/relax tolerances** (i.e., system design): It was noted that this strategy was used in TOPEX

Complex Response Signatures



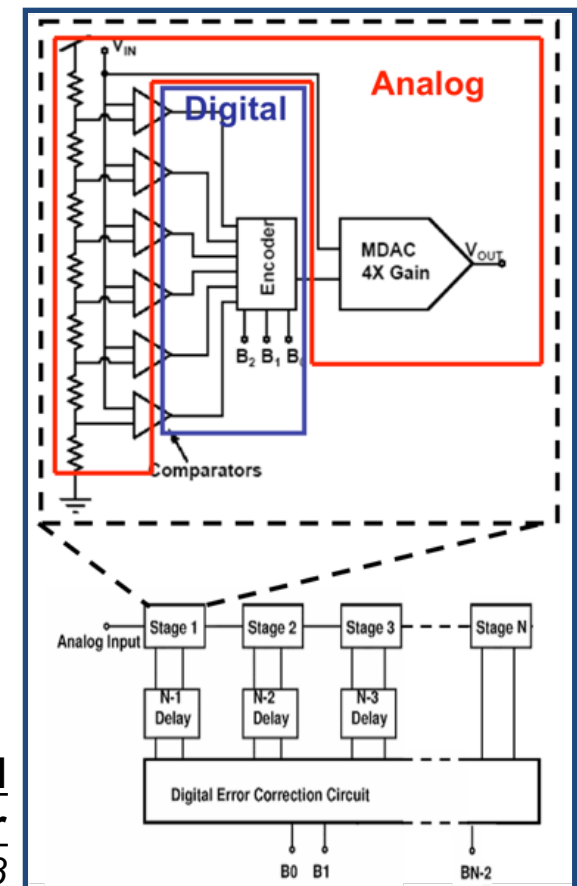
- Almost 30 years later, there is no single, standard metric for SEE in analog and mixed-signal (AMS) systems as the effect of an SEE is dependent on the **topology**, **function**, and the **operating mode**



- If analog functionality can be done with digital technology, it will be!
- However, the ability to put entire systems on a chip has increased the demand for mixed analog/digital (mixed-signal) circuits – AMS is argued to have the highest share of the IC market
- Most SoCs require some analog – processes usually have a separate and higher VDD specifically for analog
- Single-event effects (SEE) present challenges for AMS systems
 - *single-event transients (SET) are subject to cross-domain response mechanisms*
 - *SE mechanisms may be difficult to identify due to complex signal paths*

Block Diagram of a Pipelined Analog-to-Digital Converter

Olson 2008

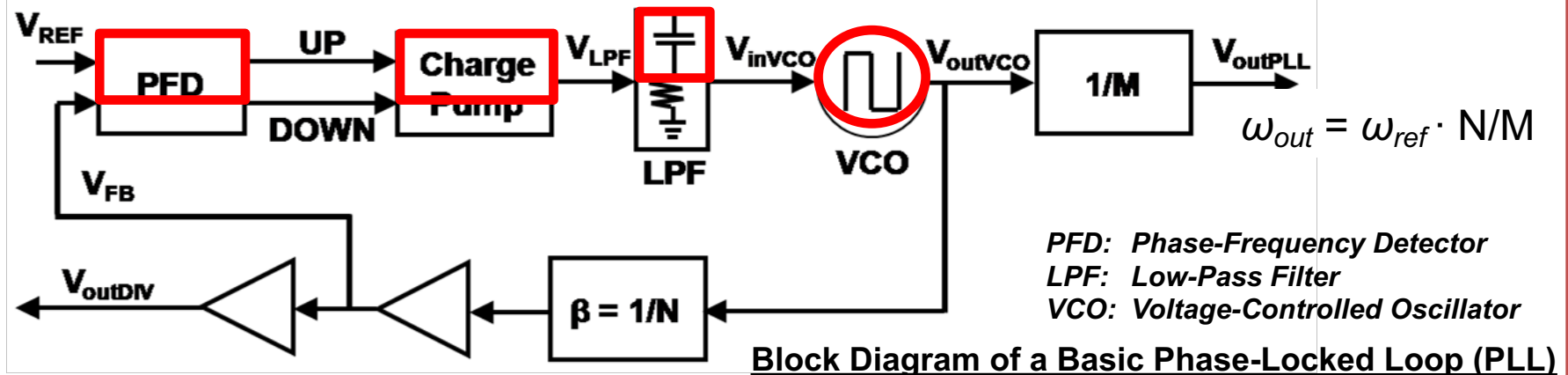


Cross-Domain Response Mechanisms



- Mixed-signal circuits are required to bridge analog and digital domains - consequently, designs are often subject to a variety of response mechanisms
 - *steady-state and transient*
 - *low-frequency and RF*
 - *digital noise and sensitive analog components*
- Single-events are subject to all interactions

Phase → Digital (V) → Analog (I) → Analog (V) → Frequency

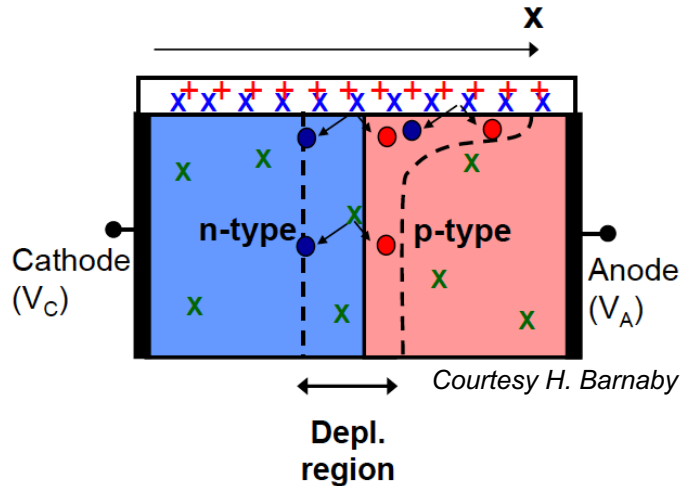


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Total-Ionizing Dose Effects



Total-Ionizing Dose (TID) in Microelectronics

Semiconductor device dielectrics:

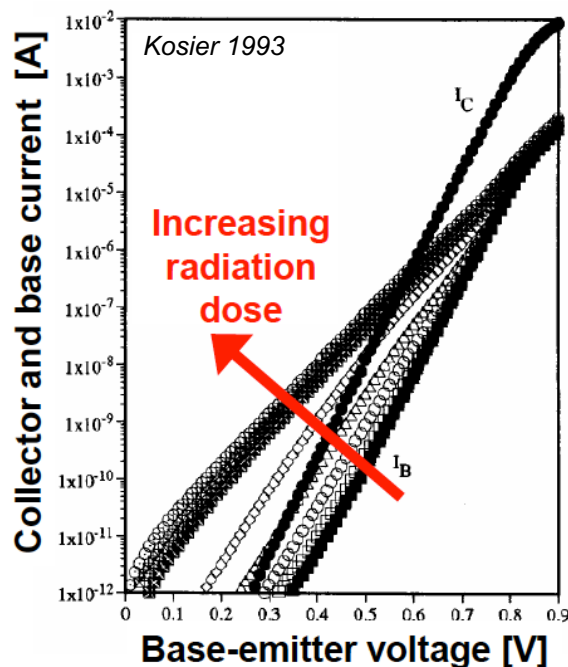
- **Interface traps (N_{it})** increase the recombination rate in the depletion region
- **Fixed oxide traps (N_{ot})** increase the depletion region, thus enhancing recombination
- **Trap defects** increase the generation in RB junctions

In **BJTs**, TID damage to oxide dielectrics leads to:

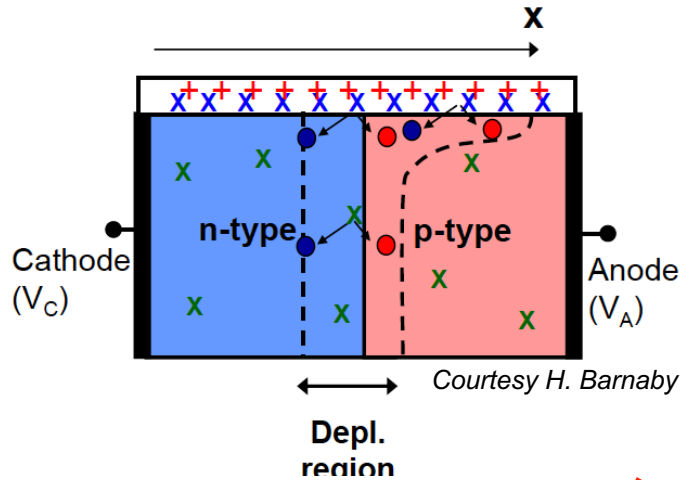
- Excess base current (via enhanced recombination with traps and beta degradation)
- Increased collector current in *npn* devices due to increased emitter area (via surface inversion from N_{ot})
- Increased reversed leakage current from collector to base (CB) due to increased carrier generation (via traps) in CB junction

Enhanced Low-Dose-Rate Sensitivity (ELDRS)

- Larger TID effects observed at low dose-rates (impacts testing methodologies)
- Primarily affects lateral bipolar devices



Total-Ionizing Dose Effects



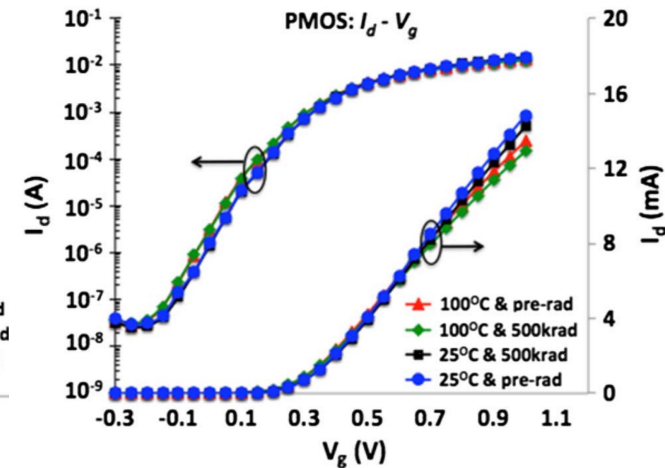
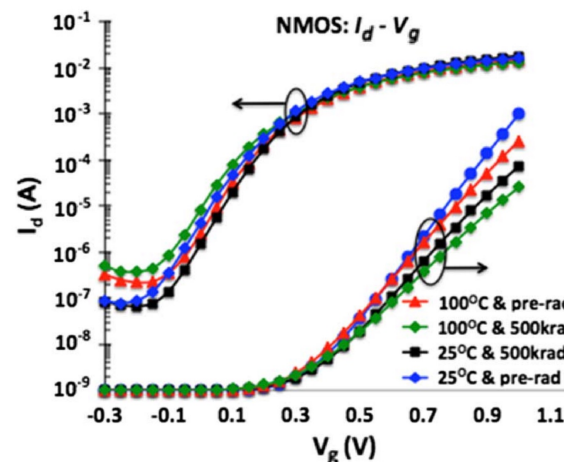
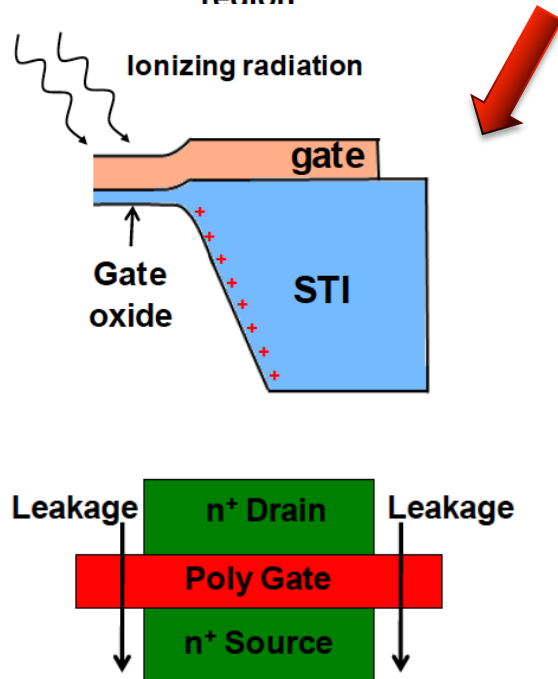
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In **CMOS**, TID leads to:

- Threshold voltage (V_t) shifts, sub-threshold slope reduction, and mobility degradation in older CMOS technologies
- Increase intra-device (edge) leakage in nMOS transistors (both old and advanced SOI technologies)
- Increased inter-device leakage in parasitic n-channel devices
- Increased static supply current



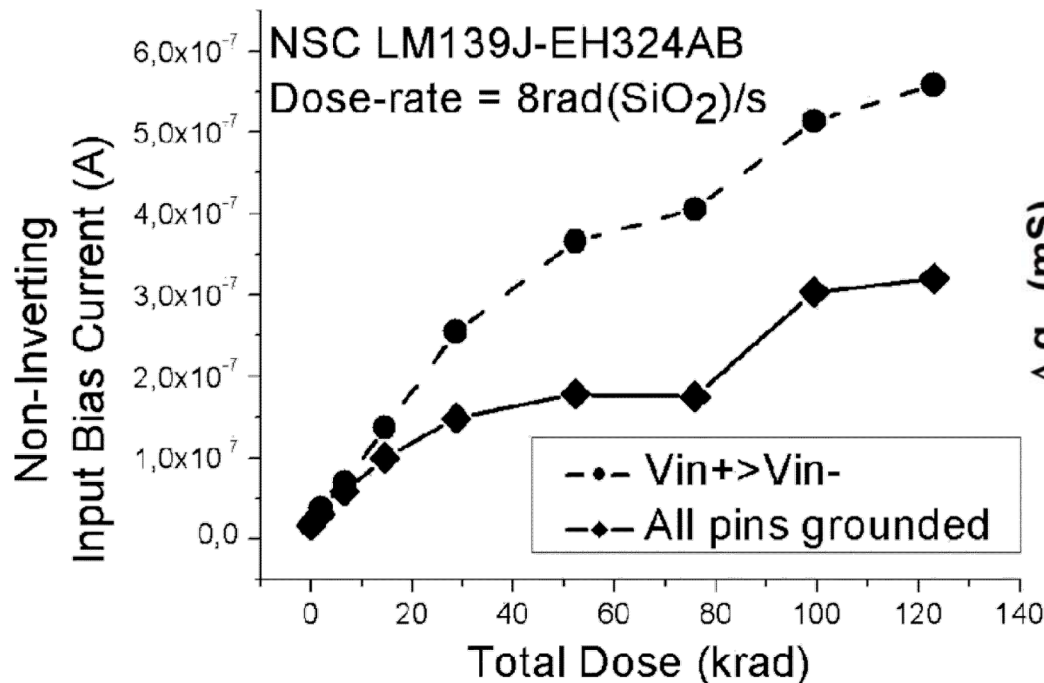
Jagannathan 2013

TID in Analog Circuits

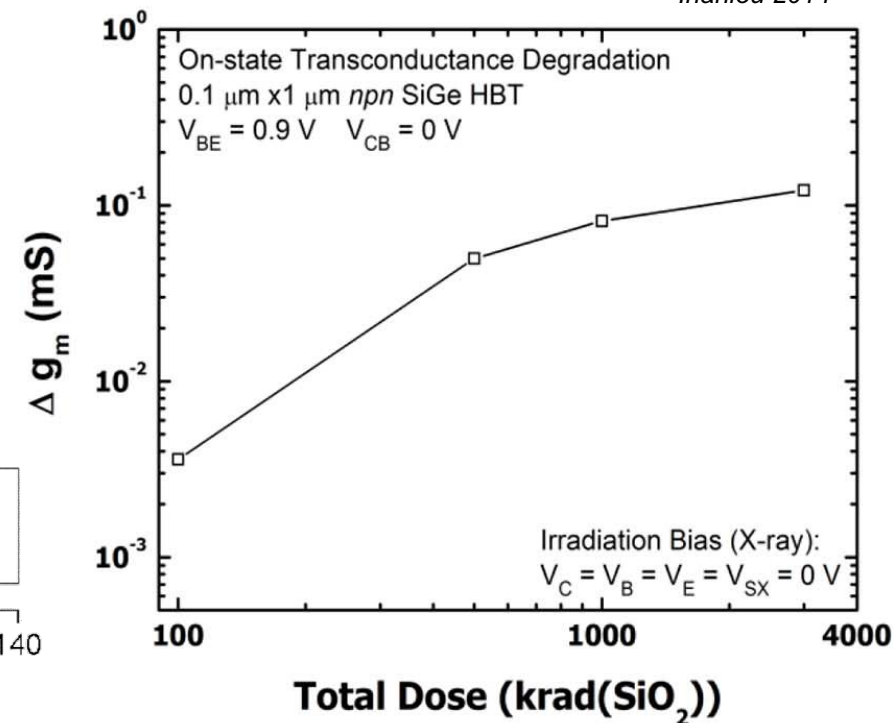


Mismatch and degradation in AC parameters due to TID tend to be problematic for analog and RF circuits

Bernard 2006



Inanlou 2014

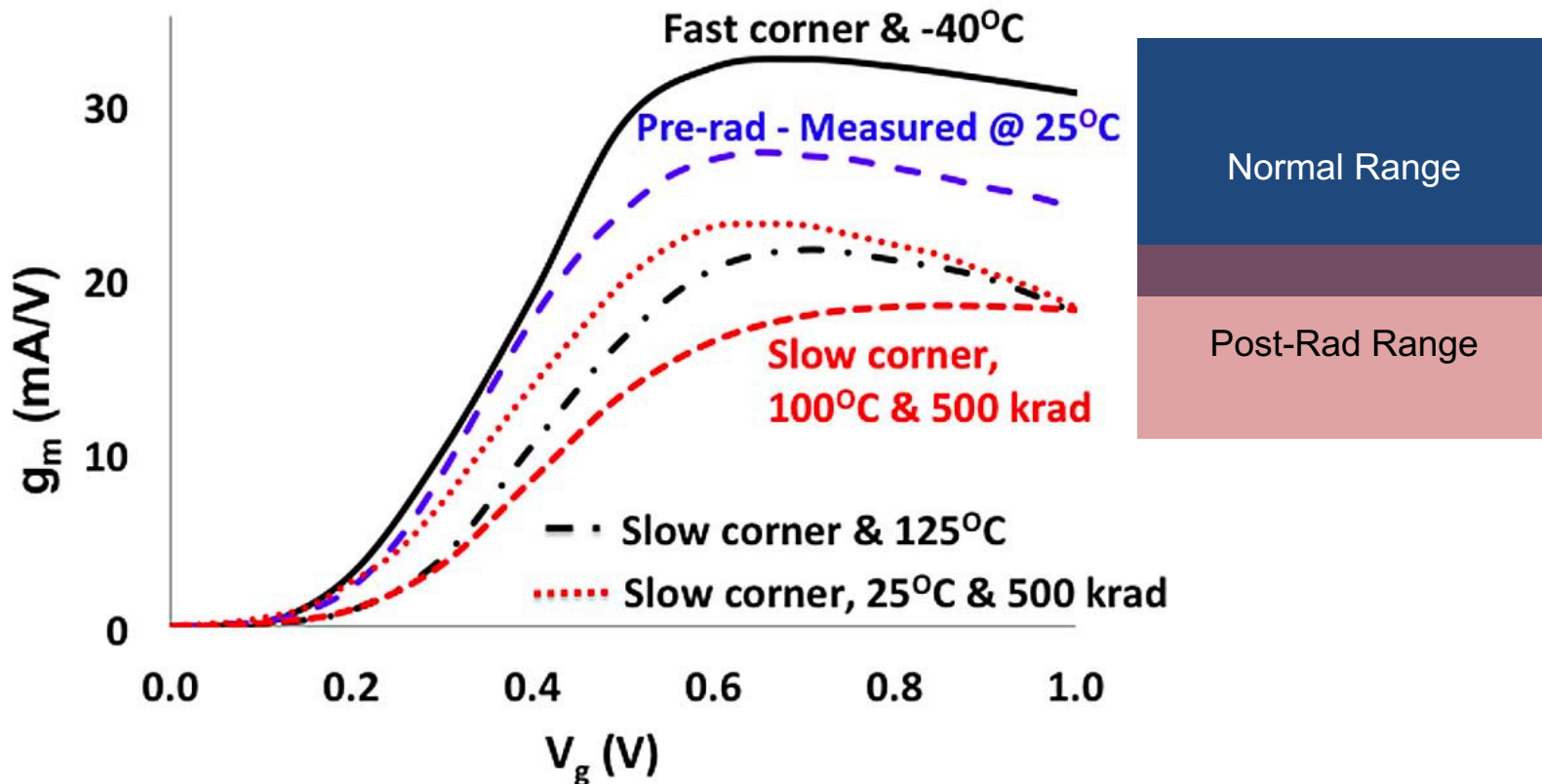


Importance of Temperature



High Performance RF circuits tend to be ultra-sensitive to TID due to the tight design margins (process, voltage, temperature, radiation)

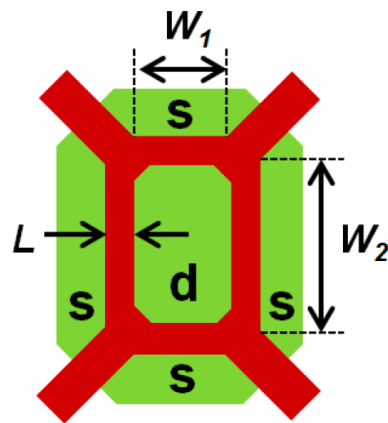
Process-Voltage-Temperature (PVT) and TID Analysis of a Commercial RF 45 nm Process Jagannathan 2013



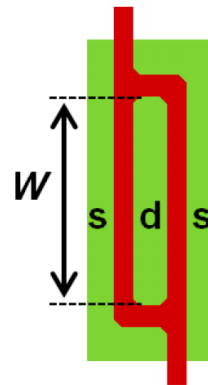
TID Mitigation Through Transistor Layout

- The most common TID mitigation approach is through individual transistor layout
- **Edgeless transistor layout** eliminates the radiation-induced sidewall channel leakage in nFETs and reduces trapped charge in the field oxide bordering the channel that can contribute slightly to threshold voltage shifts

(a) *Enclosed*

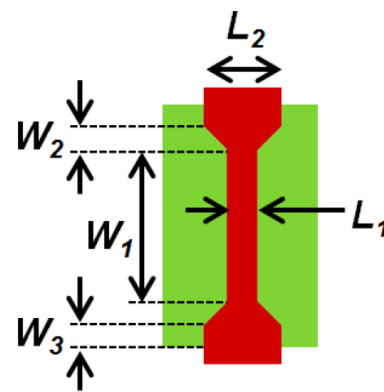


(b) *Multi-finger enclosed*



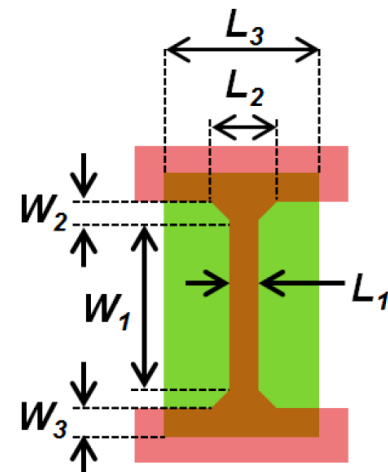
Poly

(c) *Dog bone*



Active

(d) *Edgeless dog bone*

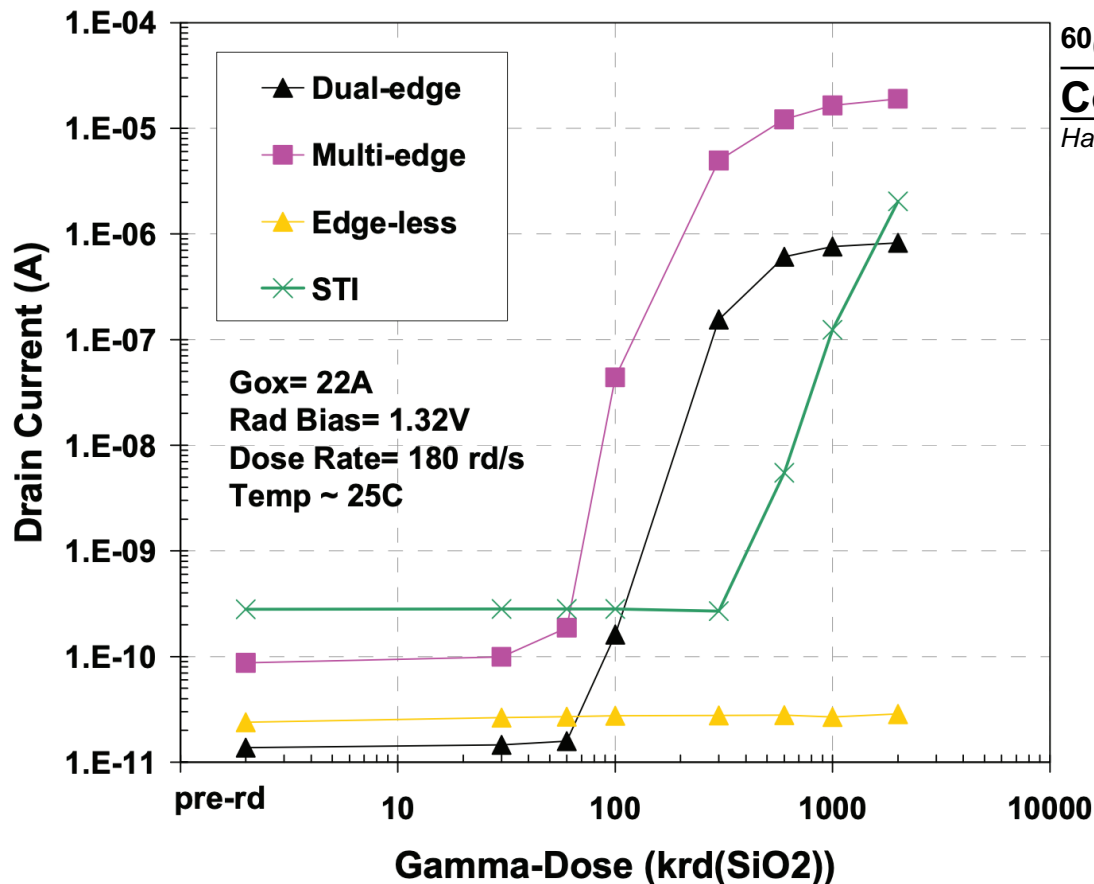


Atkinson 2013

Concentric Edgeless Layout



Concentric edgeless layout eliminates STI trapped-charge responsible for leakage



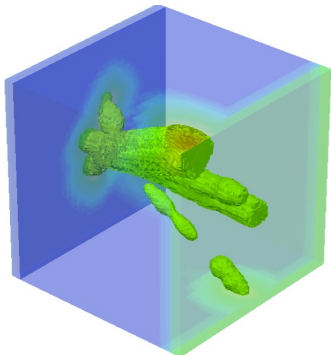
⁶⁰Co TID Evaluation of a Commercial 90 nm Process

Haddad 2008

Any cell that has not been designed for “critical node isolation” must be investigated for TID-induced failure



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Courtesy Vanderbilt



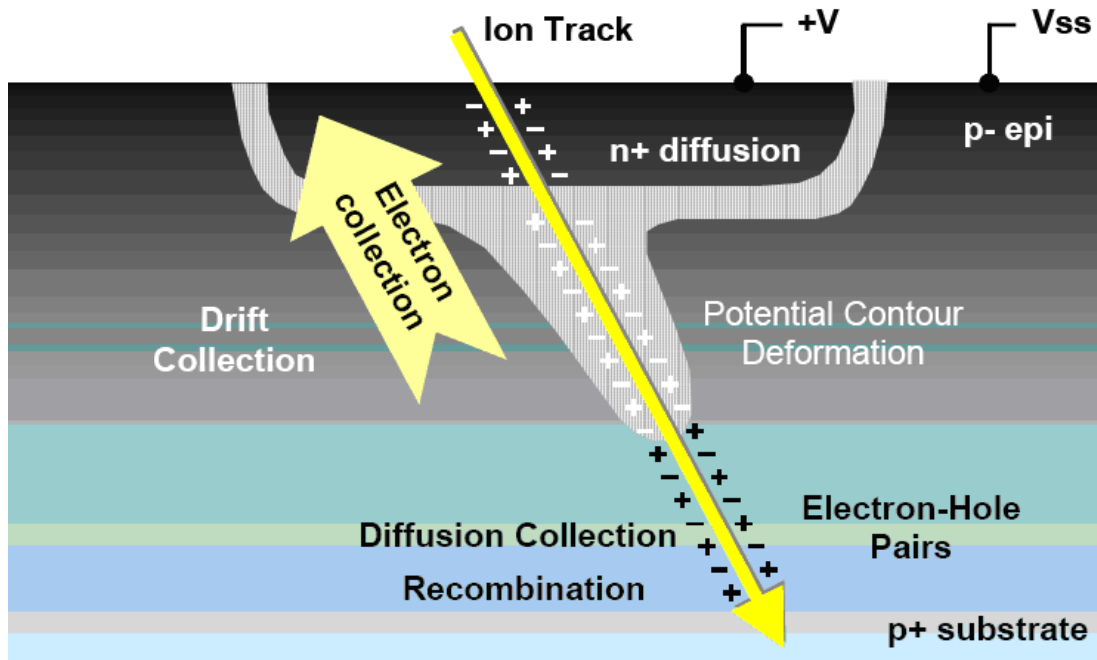
Single-Event Effects in Microelectronics

Single-Event Effects (SEE):

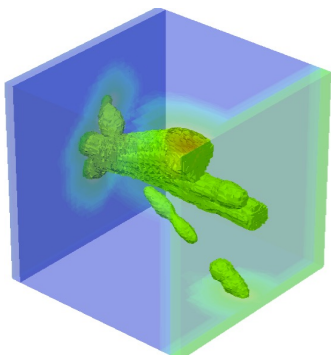
- Caused by the interaction of a single energetic particle

Ionizing Particles:

- Heavy ions from deep space (galactic cosmic rays)
- Energetic protons (trapped in the Van Allen belts)
- Neutron products (terrestrial)
- Alpha particles (from contaminants)



Example of Ion Penetrating Reverse-Biased p-n Junction

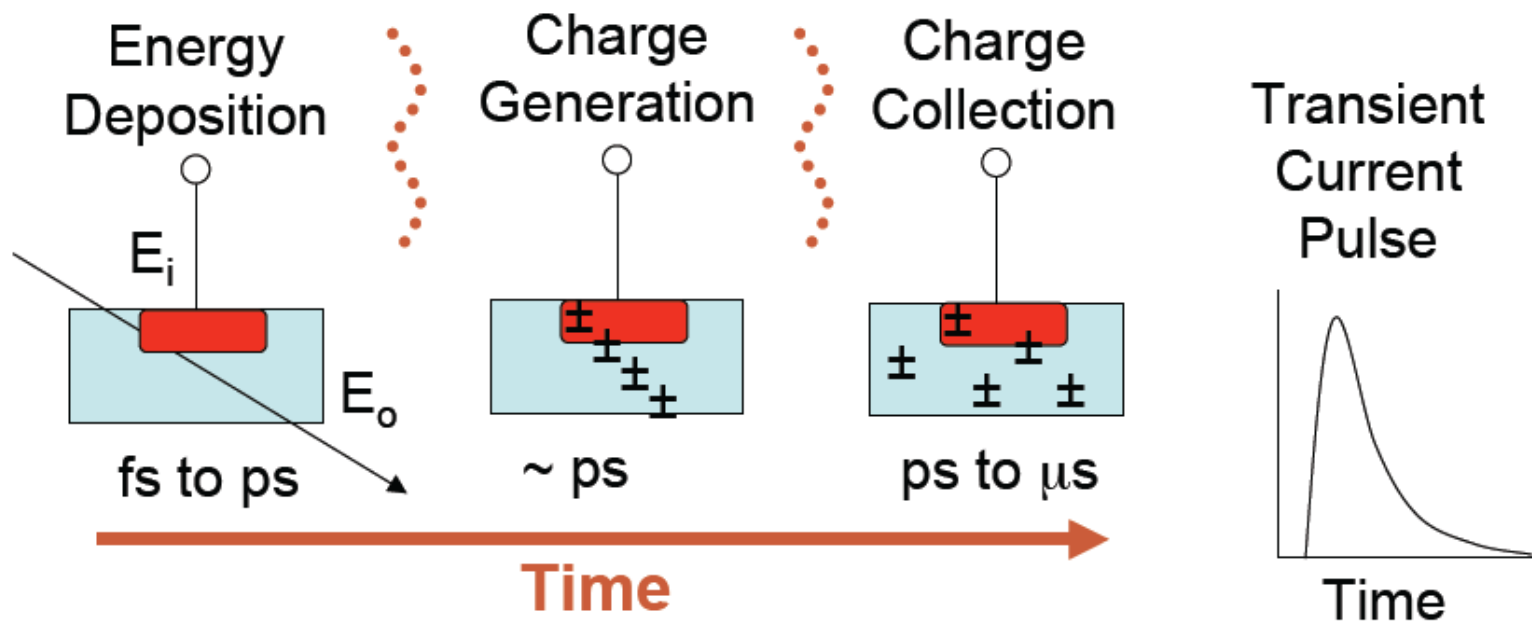


Courtesy Vanderbilt

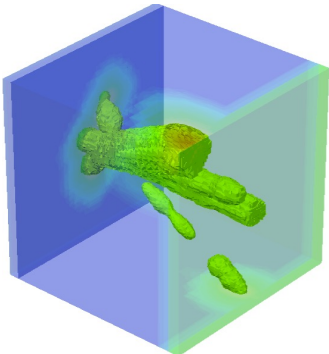
Single-Event Effects in Microelectronics

Single-Event Effects (SEE):

- Caused by the interaction of a single energetic particle
- SEE are determined by:
 - Charge generation
 - Charge collection
 - Circuit response



Single-Event Effects



Courtesy Vanderbilt



Single-Event Effects in Microelectronics

Single-Event Effects (SEE):

- Caused by the interaction of a single energetic particle
- SEE are determined by:
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• Types:

Non-destructive:

- Single-event upsets (soft errors)
- Single-event transients
- Single-event functional interrupt
- Multiple-bit upsets

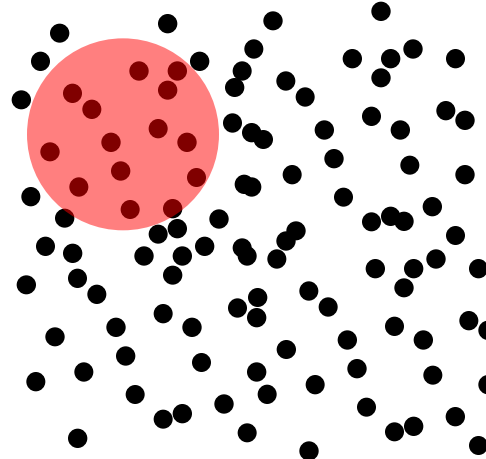
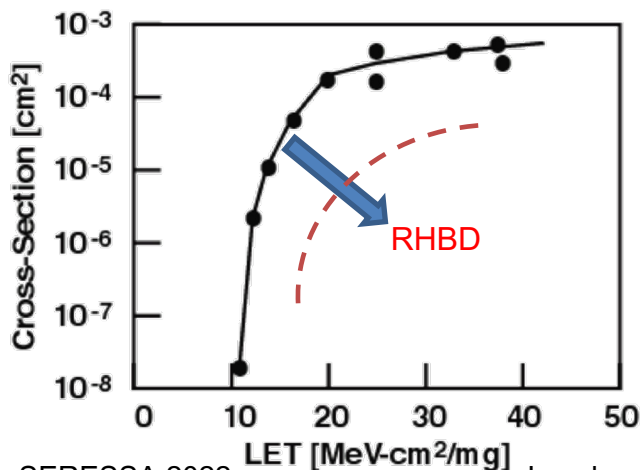
Destructive:

- Single-event latchup
- Single-event burnout
- Single-event gate rupture
- Single-event snap-back

Important Concepts:

Linear Energy Transfer (LET) & Cross-Section

Sensitive Area vs. LET



Calculation of Cross-Section

Known Aerial Density of Shots (Ions)
Ex. 10 shots/cm²

Number of shots that hit an **unknown** target

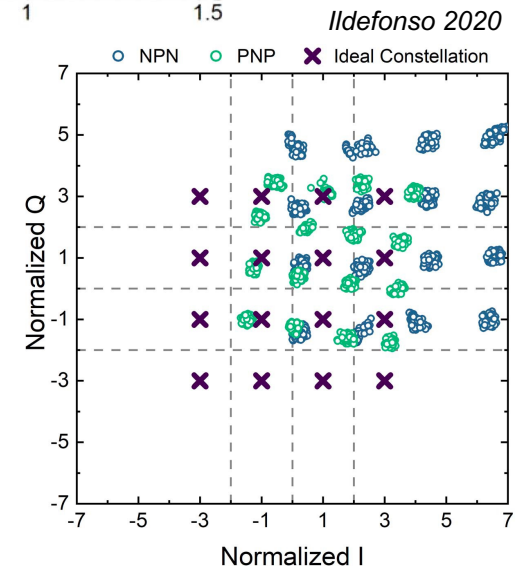
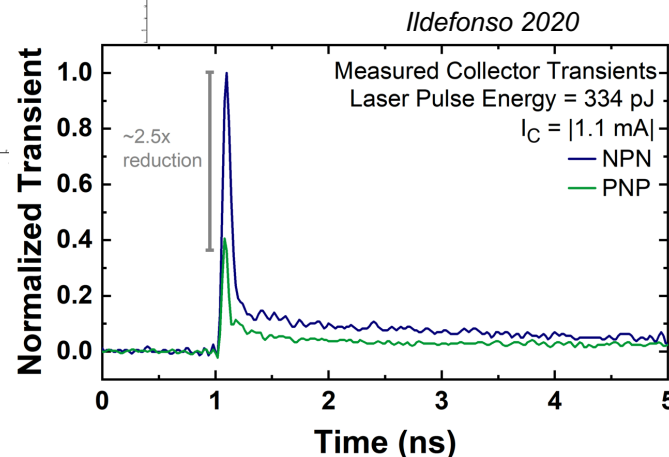
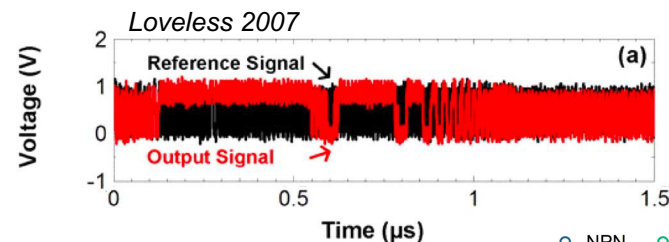
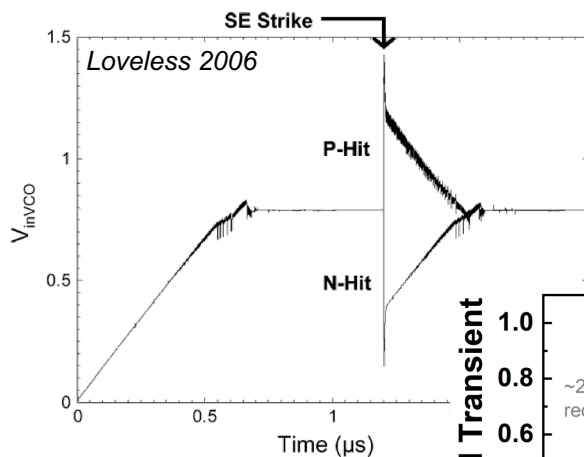
$$\text{Cross-section} = \frac{14 \text{ shots/target}}{10 \text{ shots/cm}^2} = 1.4 \text{ cm}^2/\text{target}$$

'Shotgun blast analogy' from C. C. Hafer, NSREC '09

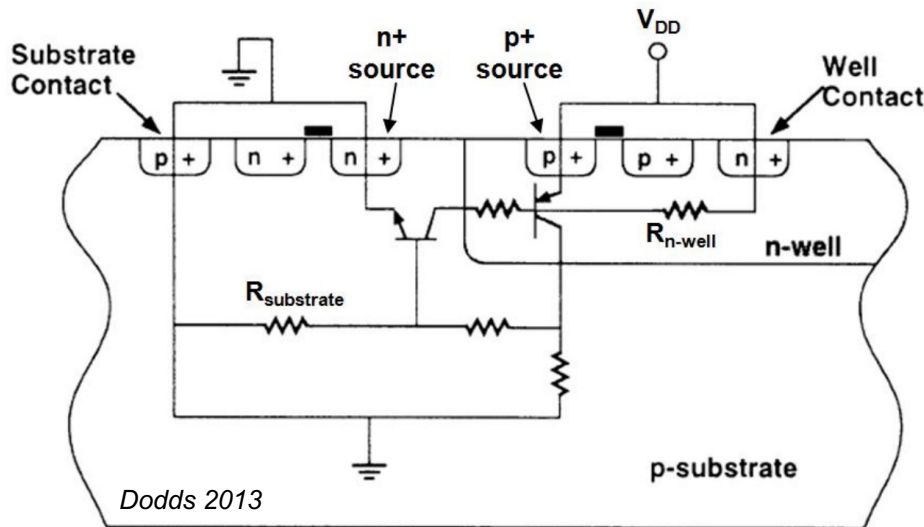
Single-Event Transients



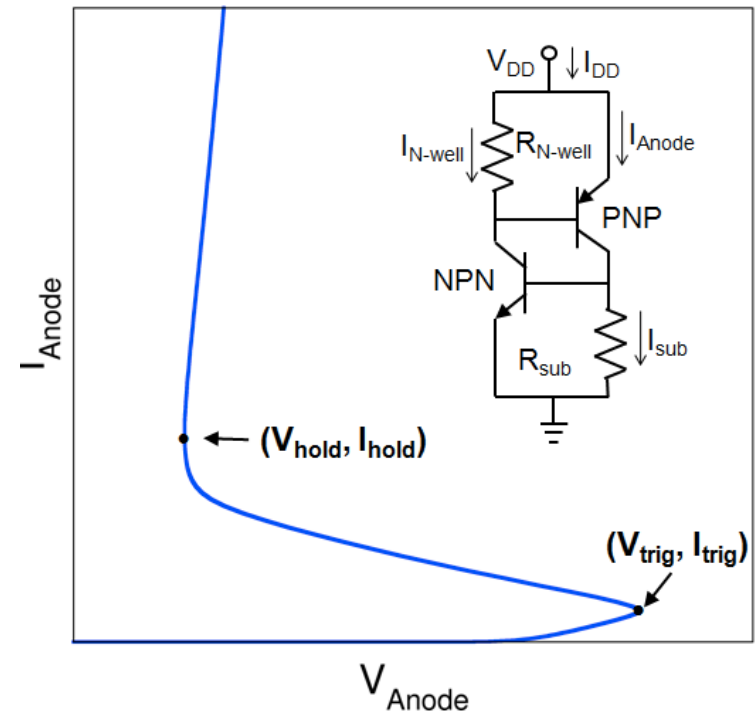
- In digital electronics, an SET may lead to a single-event upset (SEU) – *alteration of memory cell state* – that can propagate through circuit
- In analog electronics, a single-event (SE) particle strike results in a single-event transient (SET)
 - *Competes with legitimate signals or perturbs functionality*
 - *Can result in a wide range of circuit responses*



Single-Event Latchup

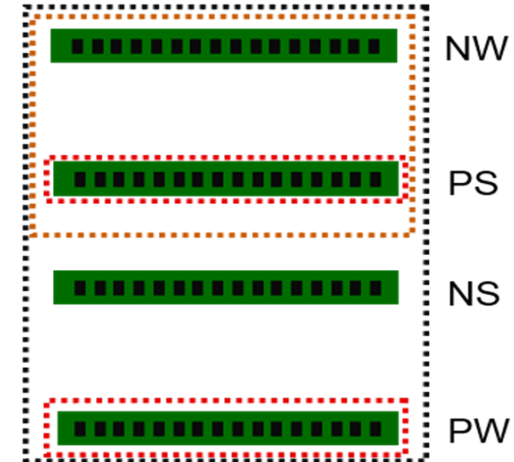
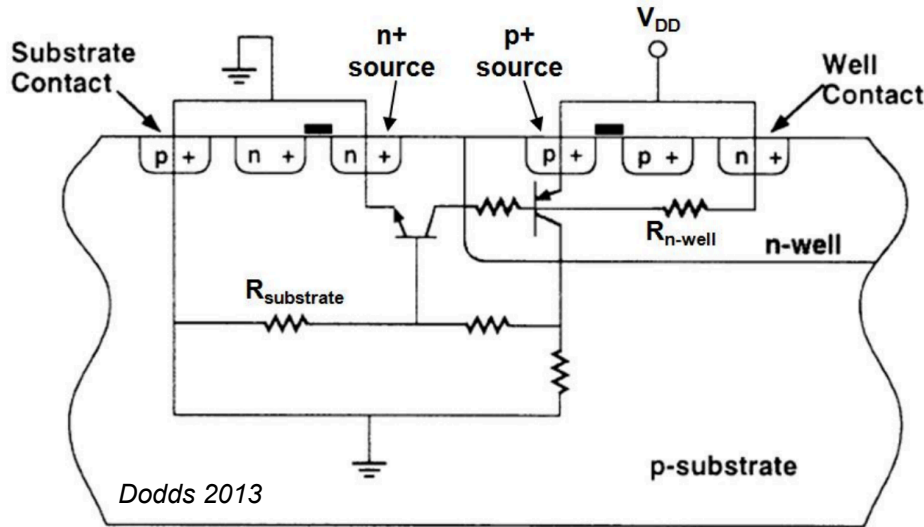


Cross-section of typical CMOS technology showing **parasitic thyristor** that can be triggered into low impedance state



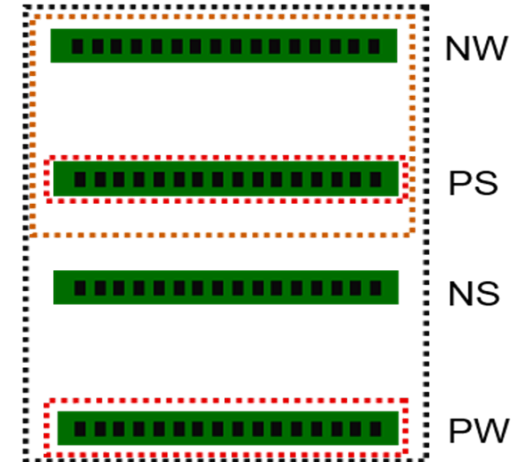
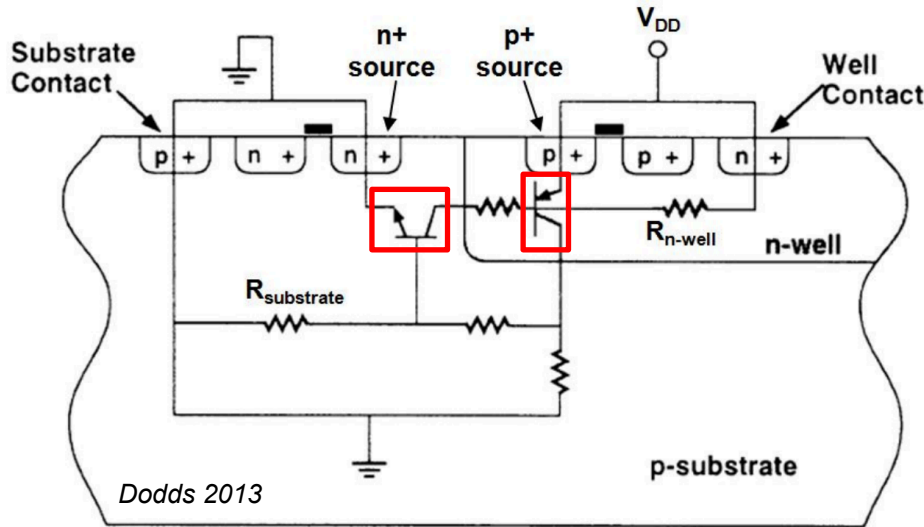
- Latchup occurs when parasitic *p-n-p-n* regions (composed of cross-coupled *p-n-p* and *n-p-n* BJTs) are activated by an energetic ionizing particle
- The collector of each BJT is connected to the base of the other, creating a positive feedback loop
- Latchup can occur when:
 - both BJTs conduct, creating a low-resistance path between V_{DD} and V_{SS}
 - the product of the gains in the BJTs in the feedback loop is greater than 1

Single-Event Latchup Mitigation



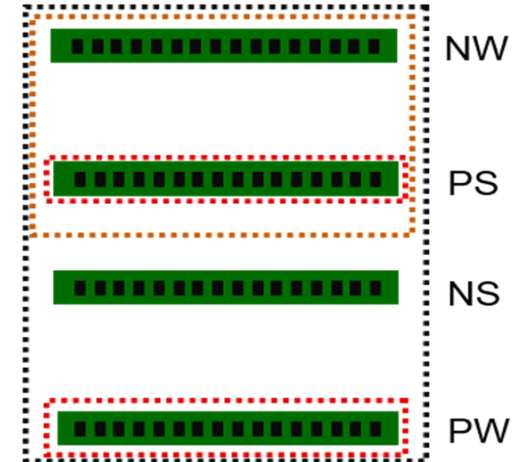
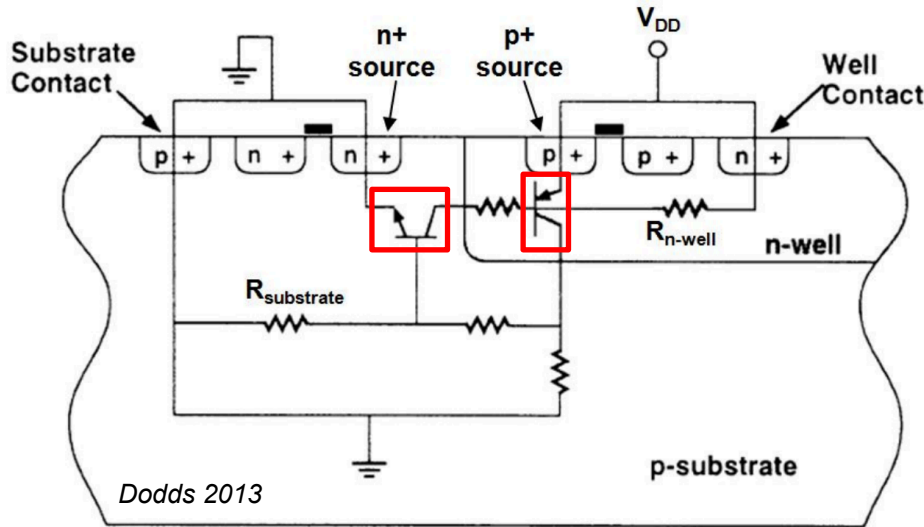
- Sensitivity depends on parasitic bipolar gains and well/substrate resistances
- Mitigation of SEL involves

Single-Event Latchup Mitigation



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- Mitigation of SEL involves
 - 1) *reduction of BJT gain*

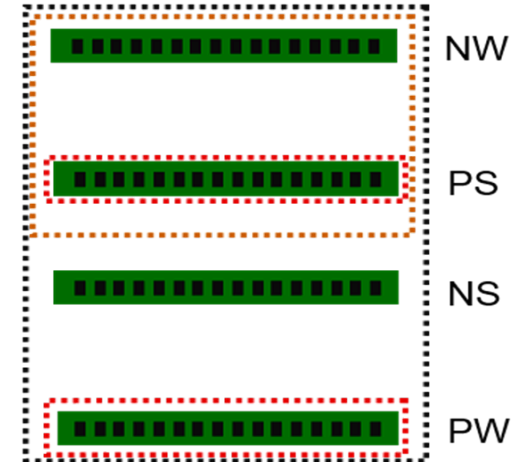
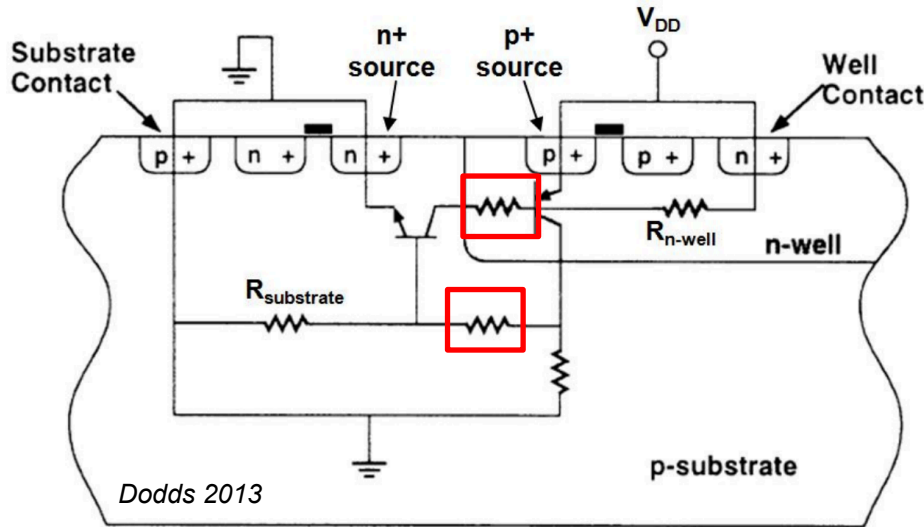
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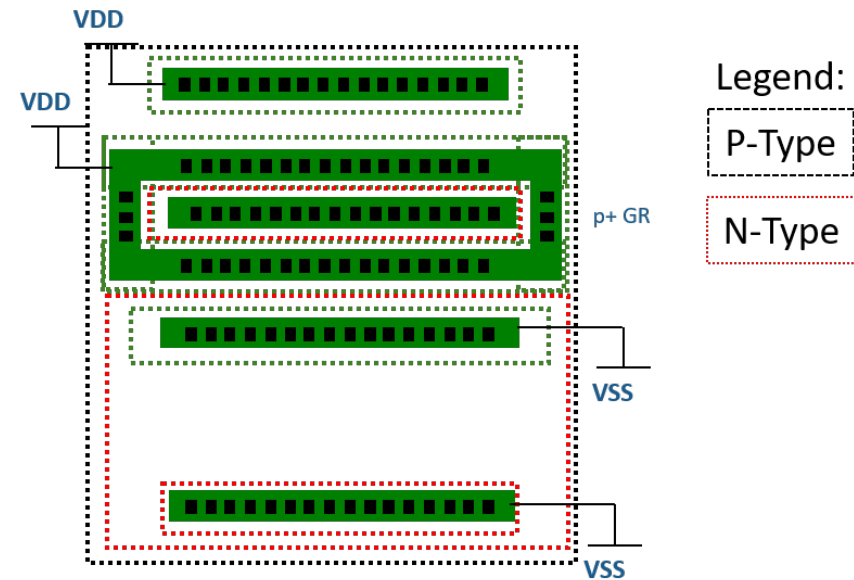
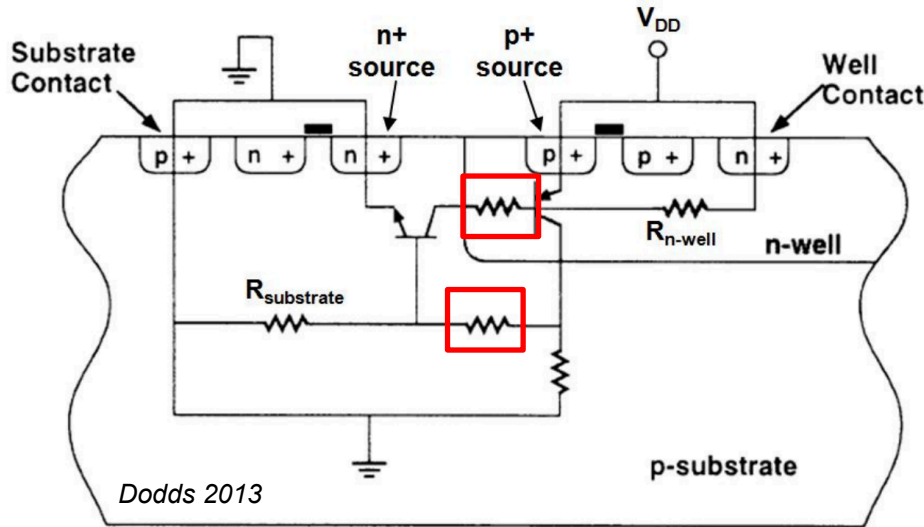
*Process engineering:
channel doping, silicide
proximity, strain*

Single-Event Latchup Mitigation

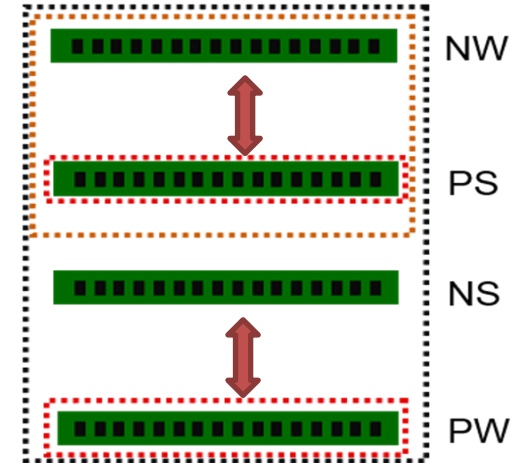


- Sensitivity depends on parasitic bipolar gains and well/substrate resistances
- Mitigation of SEL involves
 - 1) *reduction of BJT gain*
 - 2) *decoupling BJTs or increasing the coupling resistance*

Single-Event Latchup Mitigation

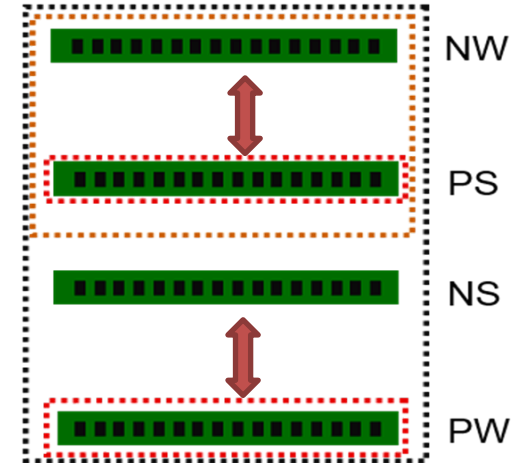
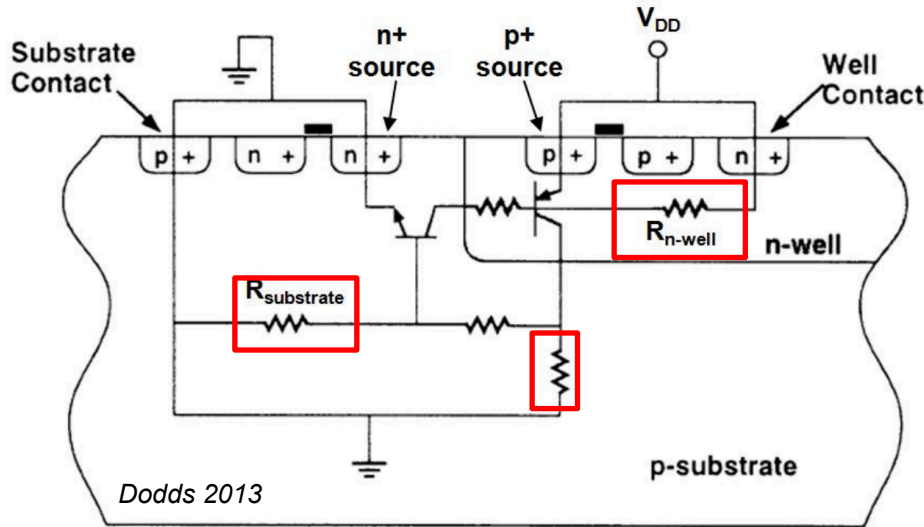


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 - 3) *decreasing resistances from the BJTs to well and substrate contacts*

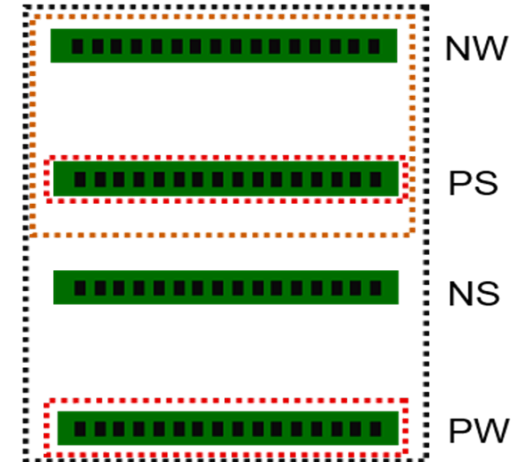
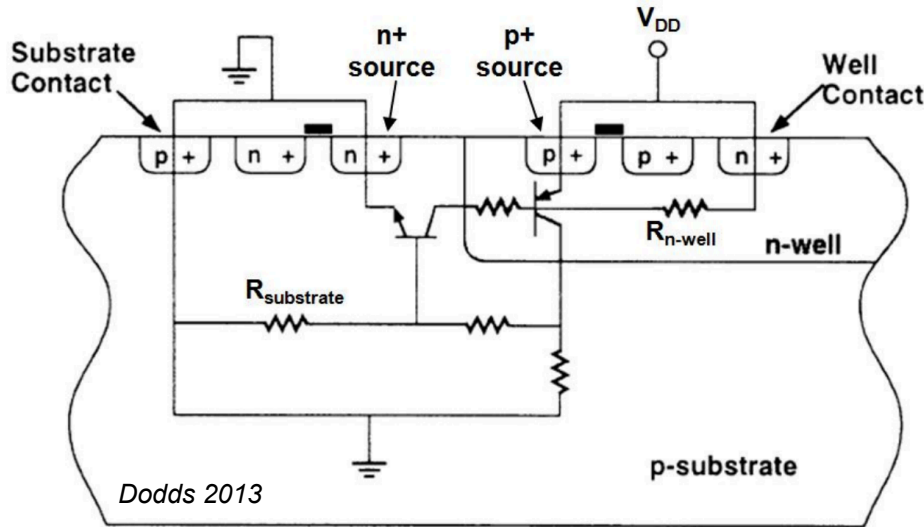
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*Decrease source-to-well spacing
Increase contact density*

Single-Event Latchup Mitigation

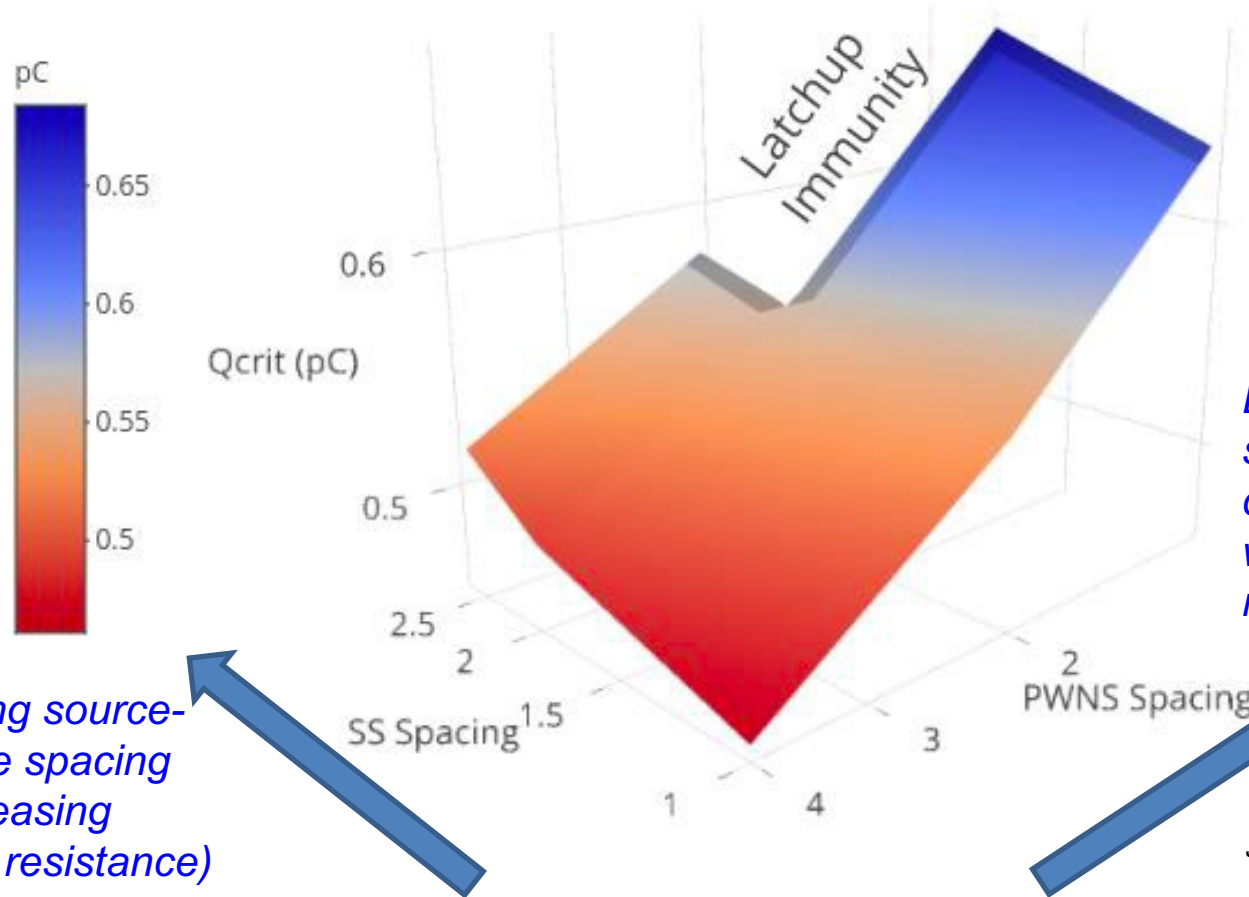


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- Mitigation of SEL involves
 - 1) *reduction of BJT gain*
 - 2) *decoupling BJTs or increasing the coupling resistance*
 - 3) *decreasing resistances from the BJTs to well and substrate contacts*
- Geometry, density, and spacing of wells, sources, source-to-well contacts, and source-to-source contacts have large impact on overall vulnerability

Single-Event Latchup Mitigation



Spacing vs. Qcrit Contour Plot



Decreasing well-to-source spacing (i.e., decreased well/substrate resistance)

Increasing source-to-source spacing (i.e. increasing coupling resistance)

Joplin 2018

Summary of SEE Mitigation Techniques



- SEE mitigation involves one or both of the following, irrespective of the technology:
 - *reducing the amount of collected charge (Q_{col}) at a metallurgical junction:*
 - layout alternatives such as guard rings, drains, or diodes (MOS)
 - n-rings, substrate-tap rings, and nested minority-carrier guard rings (BJT)
 - substrate engineering: charge blocking layers in the substrate, use of very thin epitaxial silicon layer, silicon-on-insulator (SOI)
 - addition of dummy collector for charge collection in HBT devices
 - increased substrate and well contacts (reduced substrate and well impedances)

Hardening-by-process (technology modifications)

Hardening-by-design (layout modifications)

Summary of SEE Mitigation Techniques



- SEE mitigation involves one or both of the following, irrespective of the technology:
 - *reducing the amount of collected charge (Q_{col}) at a metallurgical junction:*
 - *increasing the critical charge (Q_{crit}) required to generate an SET*
conventional, perhaps “brute force” methodology include:
 - increasing the transistor sizes (buffering)
 - increasing the drive currents
 - increasing the supply voltage
 - increasing capacitor sizes

Hardening-by-design
(layout, circuit, and/or system modifications)

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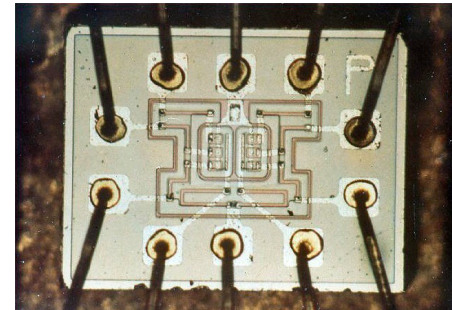
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The Big Picture

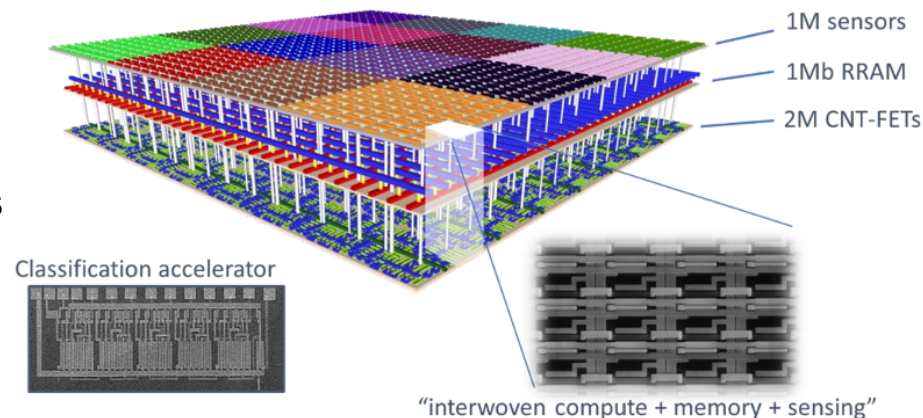
- State-of-the-art chip systems contain billions of transistors, integrated analog and digital, 3D IC stacks, and multiple voltage domains
- Critical charge can be just a few fC

Challenges for RHBD

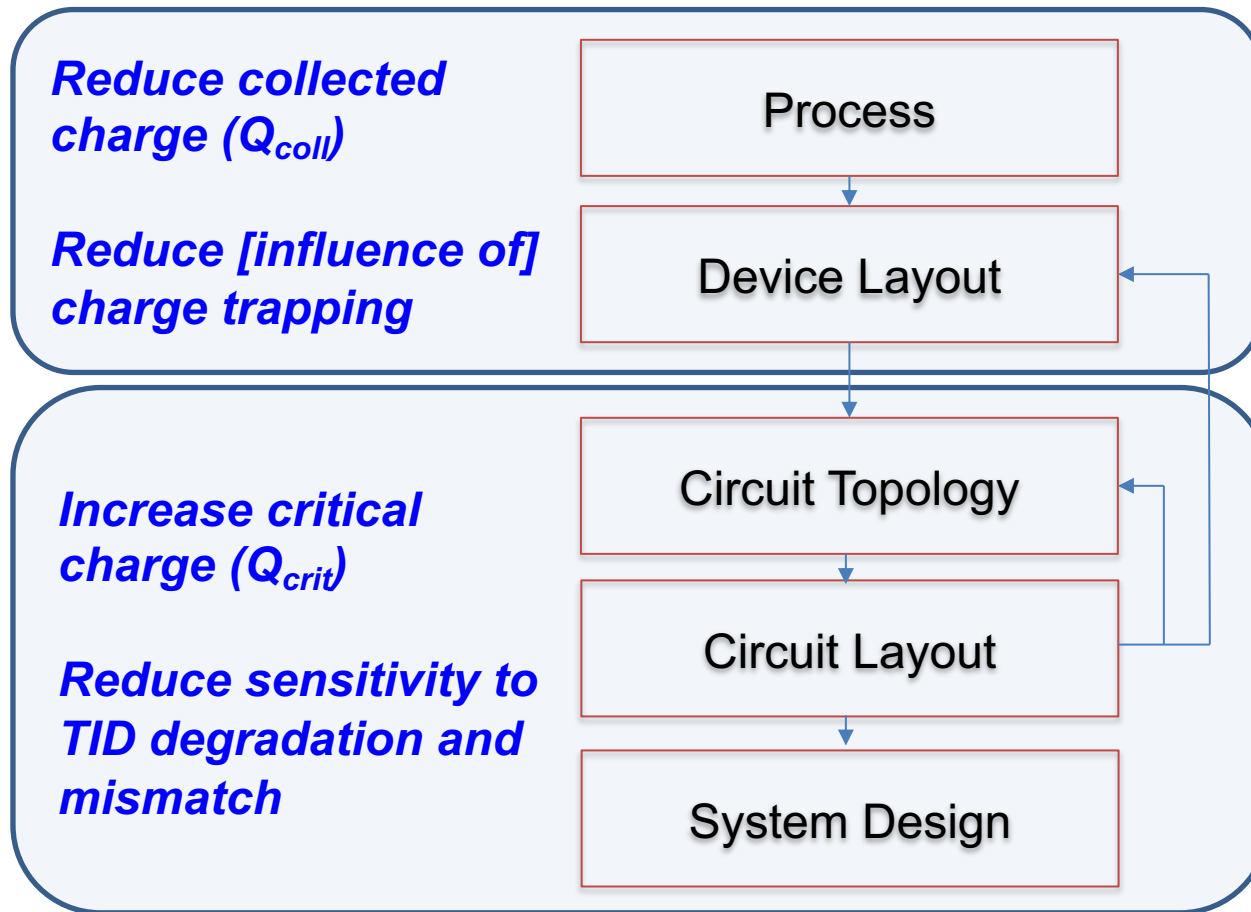
- Integration of process, layout, topology, and system-level approaches
- Architecture-level SE simulation and high-level RHBD approaches
- SEE for low-power circuits
- Development and analysis of RHBD libraries
- Effects of **charge-sharing**
- Integrated modeling, simulation and experimental analysis methodologies for advanced technology ICs



Logical NOR IC from Apollo (~1961)



3D-SoC sensor/machine learning IC from Stanford (2017)



Basic RHBD for AMS: By Process

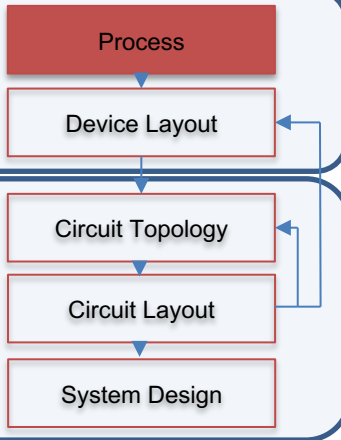


Reduce collected charge (Q_{col})

Reduce [influence of] charge trapping

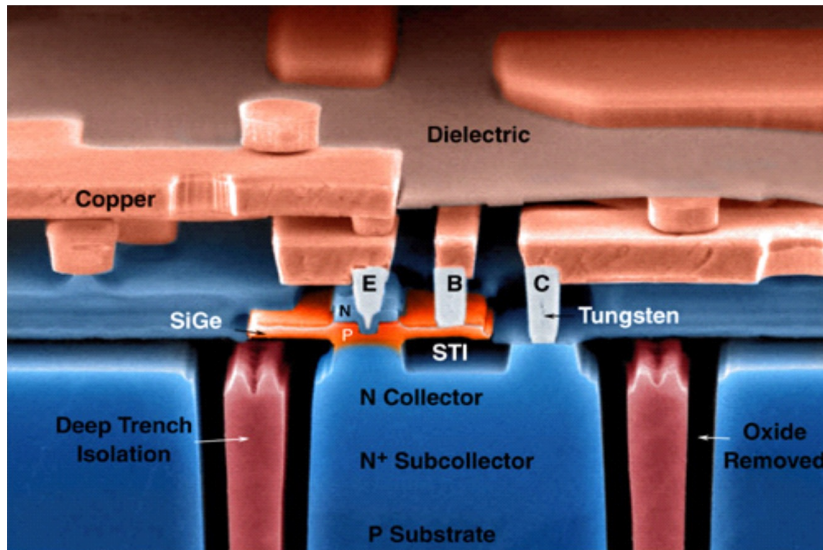
Increase critical charge (Q_{crit})

Reduce sensitivity to TID degradation and mismatch

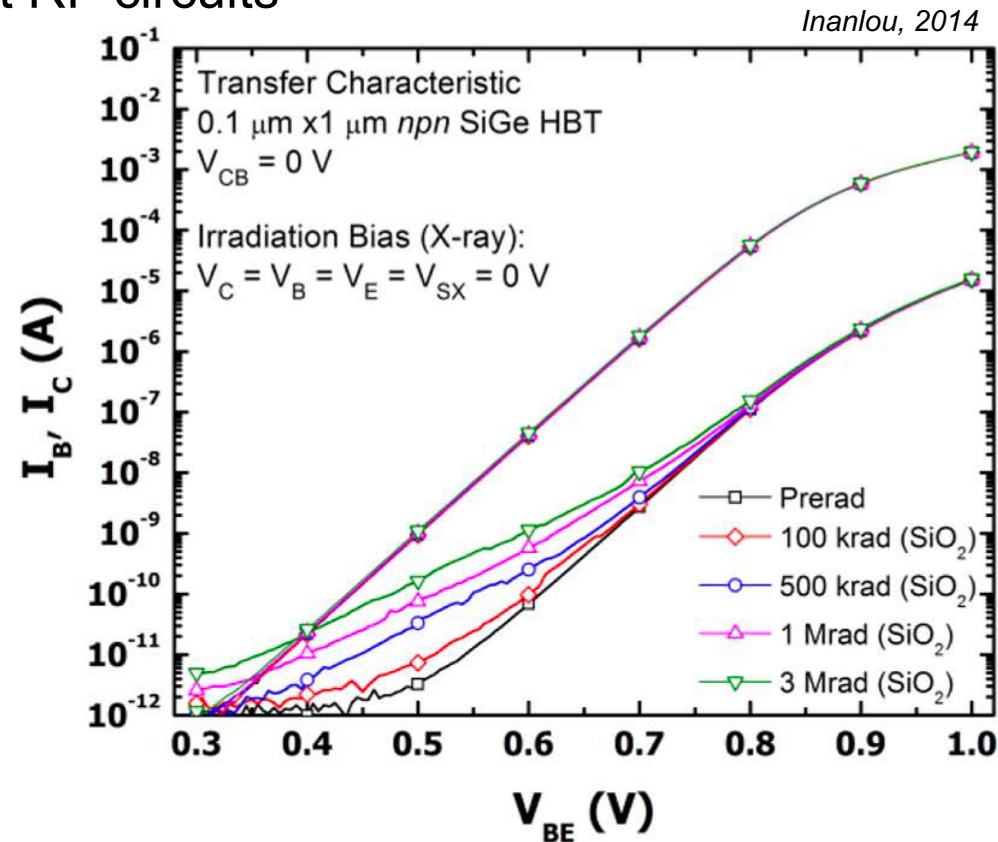


By-Process example:

Strained-enhanced SiGe HBTs (graded Ge layer in the base of a Si transistor) have emerged as an excellent alternative for TID-robust RF circuits



Cressler, 2009



Inanlou, 2014

Basic RHBD for AMS: By [Layout] Design

Reduce collected charge (Q_{col})

Reduce [influence of] charge trapping

Increase critical charge (Q_{crit})

Reduce sensitivity to TID degradation and mismatch

Process

Device Layout

Circuit Topology

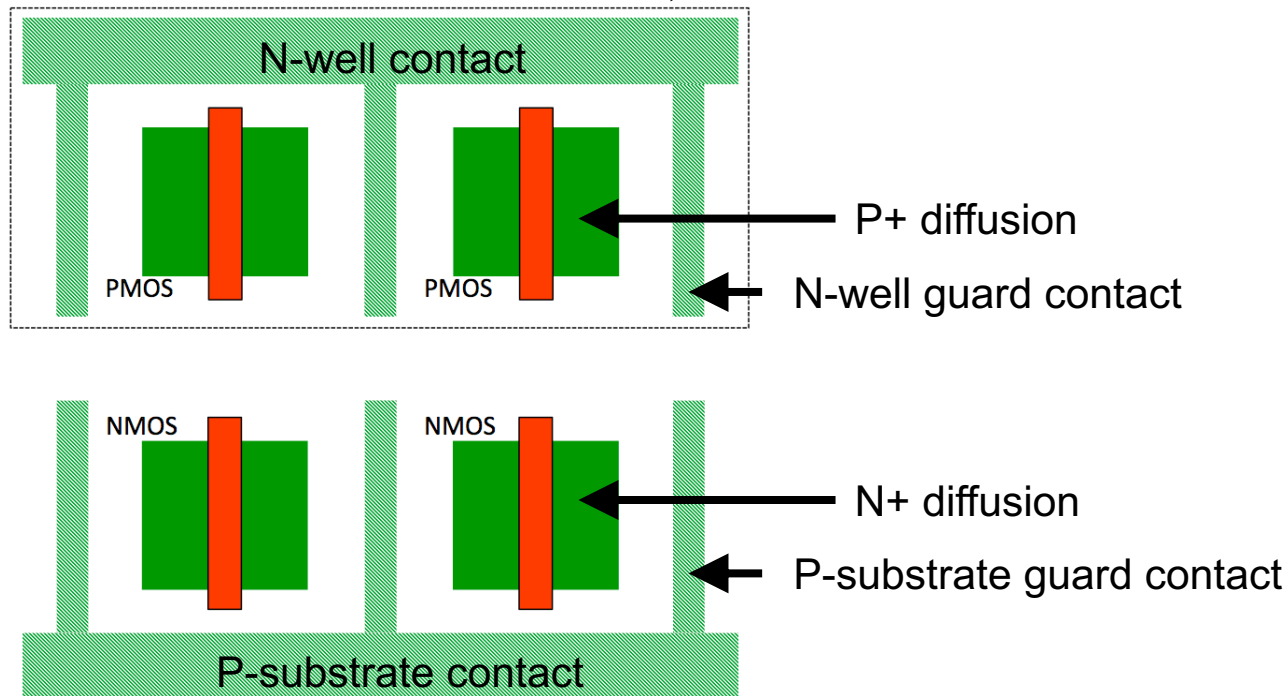
Circuit Layout

System Design

By-Design (Device Layout) example:

Guard contacts, formed from N-well and P-substrate diffusion contacts limit the charge collection at the circuit diffusions

Black, 2005



Basic RHBD for AMS: By [Circuit] Design

Reduce collected charge (Q_{col})

Reduce [influence of] charge trapping

Increase critical charge (Q_{crit})

Reduce sensitivity to TID degradation and mismatch

Process

Device Layout

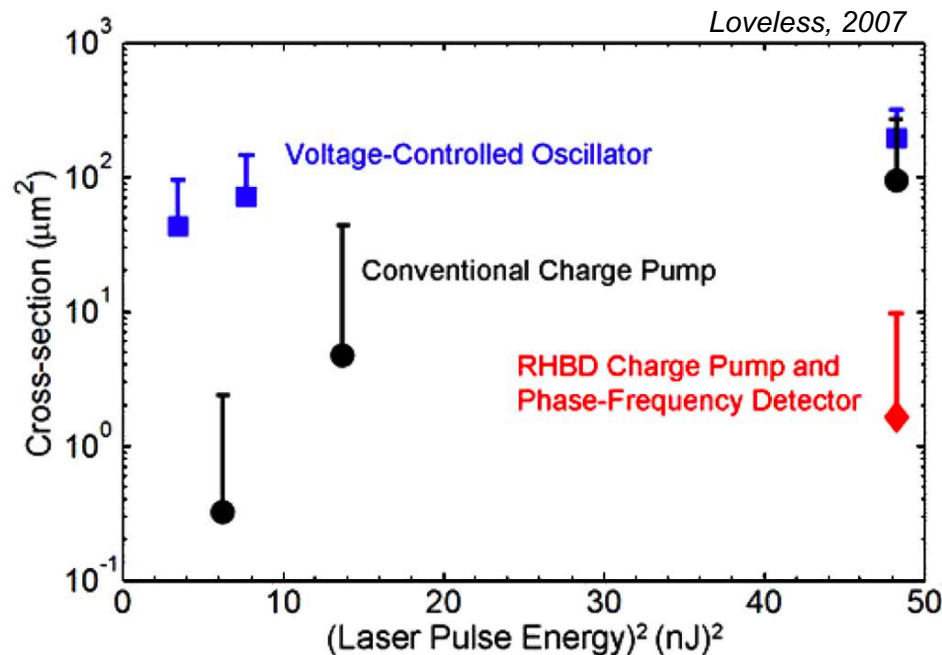
Circuit Topology

Circuit Layout

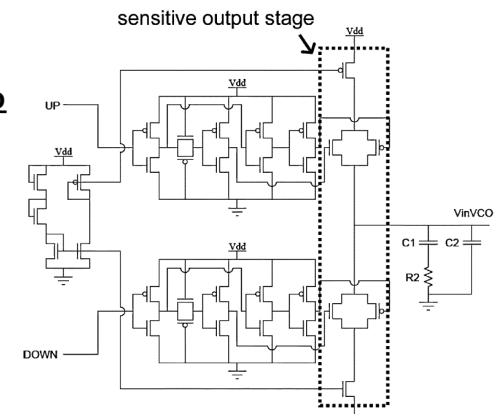
System Design

By-Design (Circuit) example:

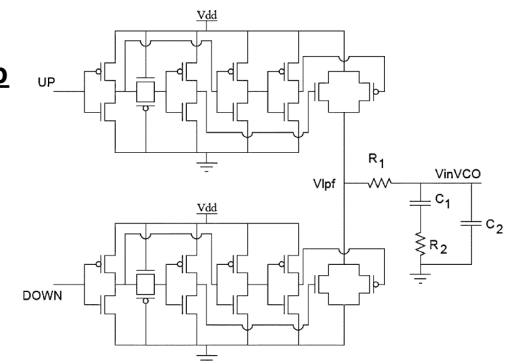
Small changes to the circuit topology can lead to large gains in SEE performance



Unhardened Charge Pump (130 nm)



RHBD Charge Pump (130 nm)



Basic RHBD for AMS: By [Layout] Design

Reduce collected charge (Q_{col})

Reduce [influence of] charge trapping

Increase critical charge (Q_{crit})

Reduce sensitivity to TID degradation and mismatch

Process

Device Layout

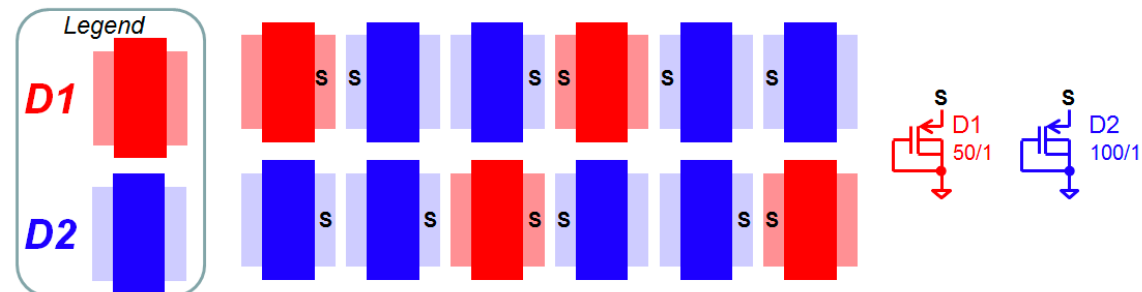
Circuit Topology

Circuit Layout

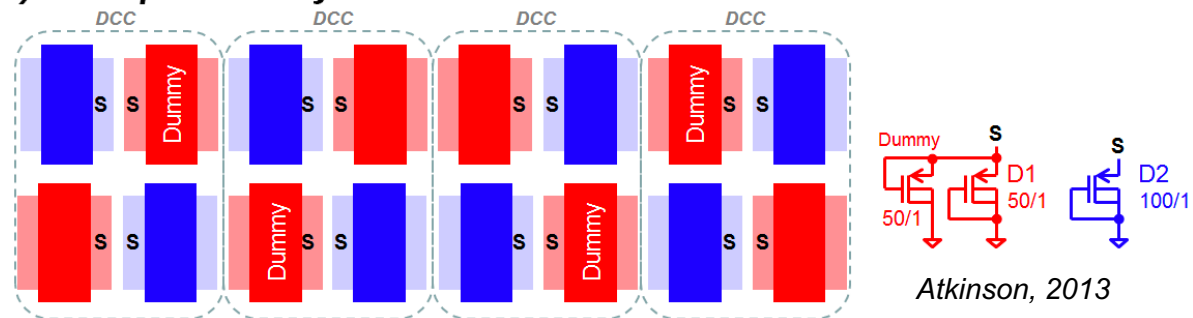
System Design

By-Design (Circuit Layout) example:

(a) Baseline quadrant layout of D1 and D2

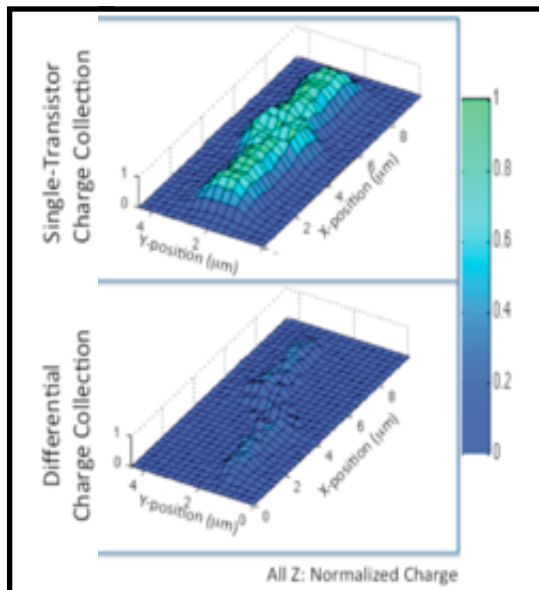


(b) DCC quadrant layout of D1 and D2



(c) Common-centroid layout of quadrants

Quadrant	transpnsQ
transpnsQ	Quadrant



Armstrong, 2010

Basic RHBD for AMS: By [System] Design

Reduce collected charge (Q_{col})

Reduce [influence of] charge trapping

Increase critical charge (Q_{crit})

Reduce sensitivity to TID degradation and mismatch

Process

Device Layout

Circuit Topology

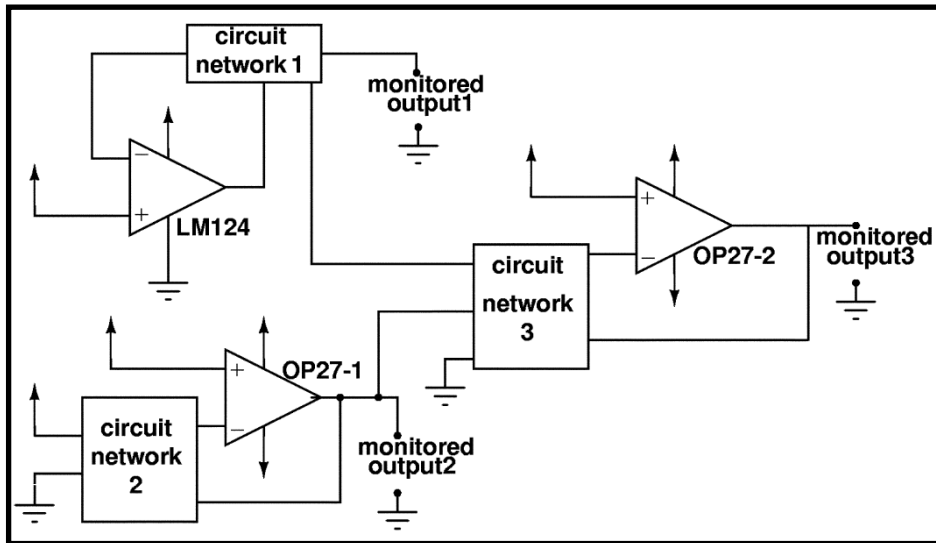
Circuit Layout

System Design

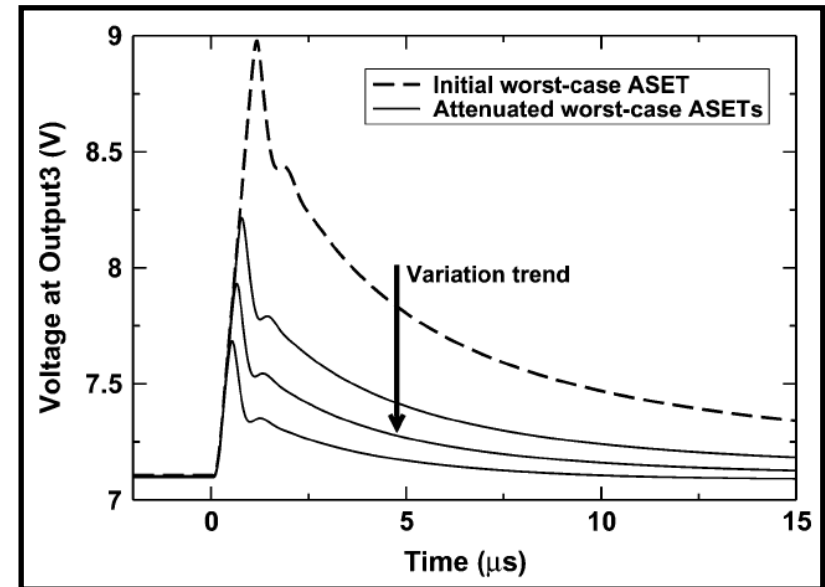
By-Design (System) example:

Low-pass filtering at system-level can effectively reduce SETs

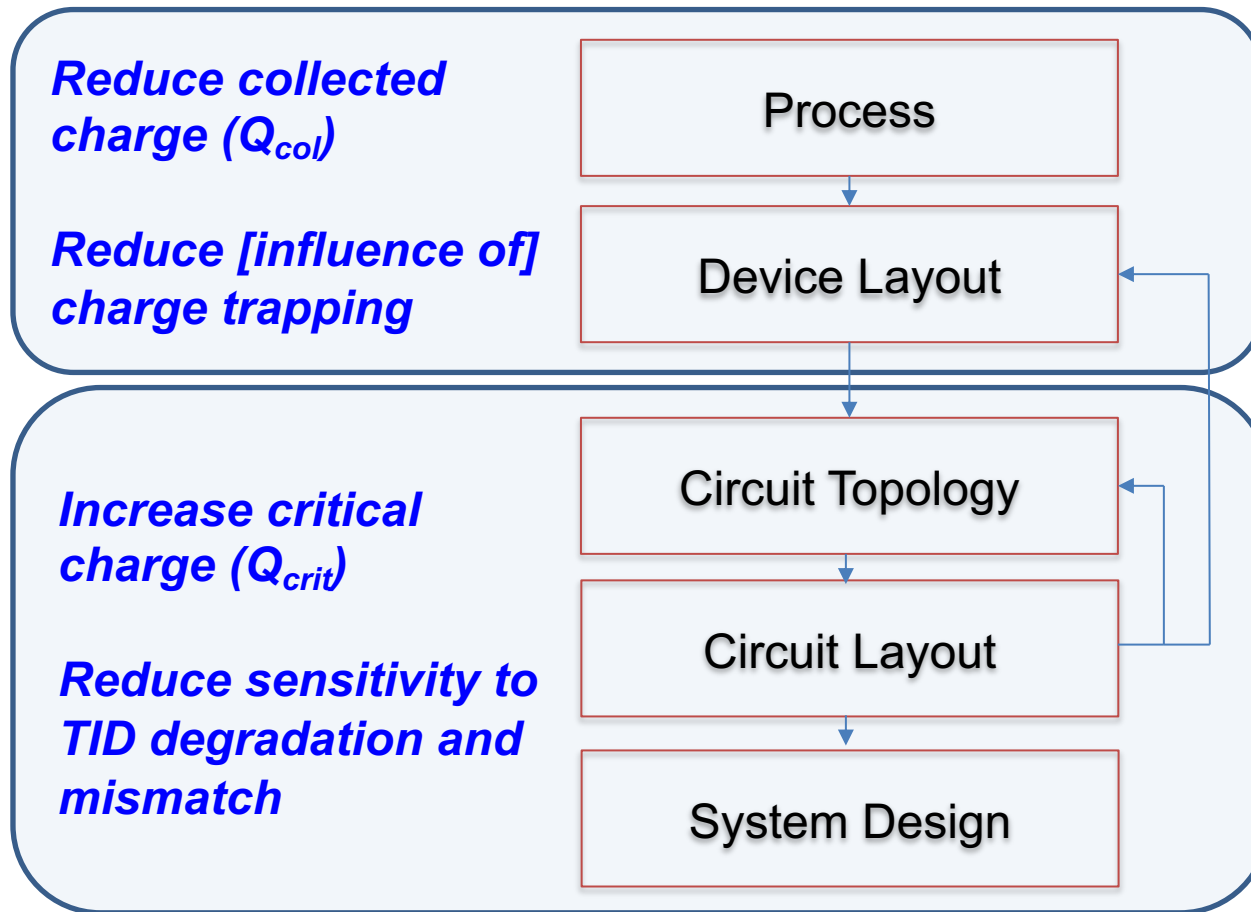
Boulghassoul, 2004



Block Diagram of Satellite Power Distribution Controller/Monitor



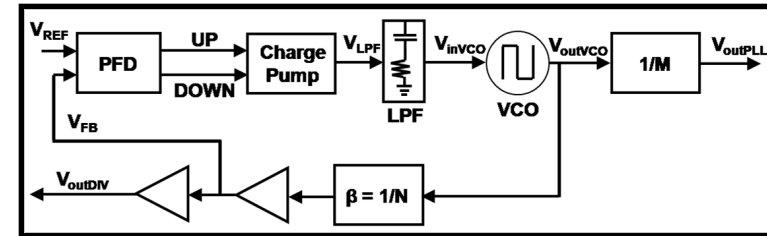
Ok, lets start to pull it all together



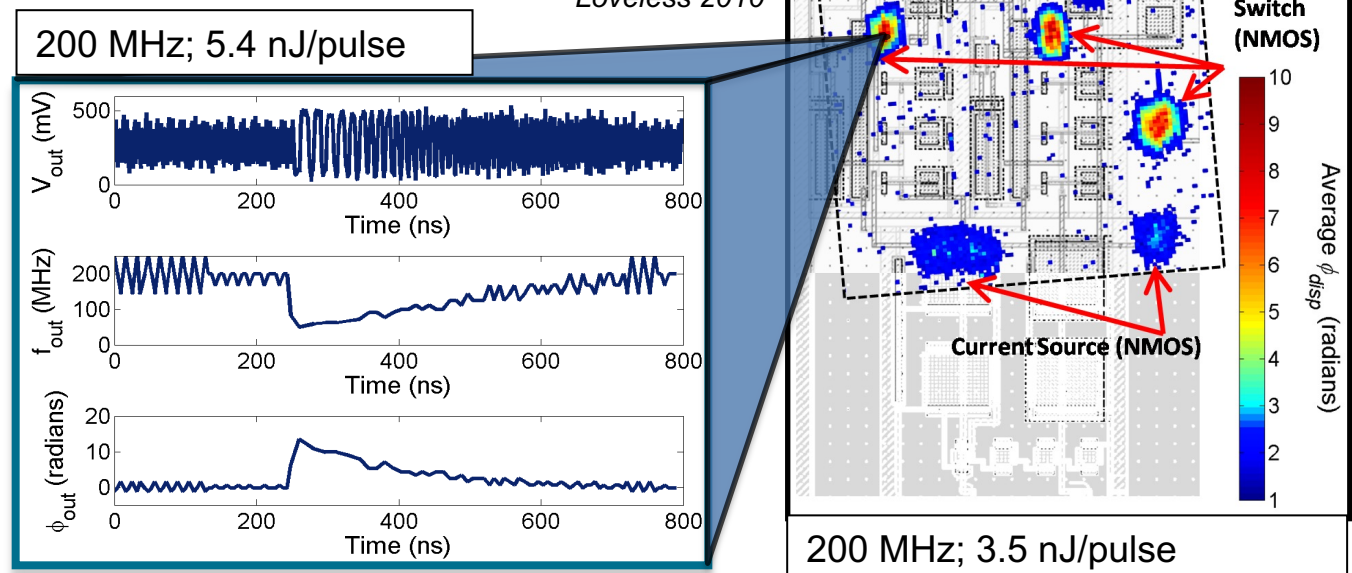
Targeted Laser Excitation



- PLL used as an example to illustrate complex inter-dependencies
- Laser SET mapping performed on charge pump sub-circuit (most sensitive block)
 - *output signals following 10 strikes per x-y location were recorded*
 - *frequency/phase transients extracted from transient output*



Two-Photon Absorption Laser-Induced SET Map of PLL Sub-Circuit (Charge Pump)



Now we know the issues, start with ... ?



- **Resistive Decoupling**

- *effectively increases the time constant seen by the two storage nodes and limit the maximum change in voltage during a single-event, thus increasing Q_{crit}*

- **Filtering**

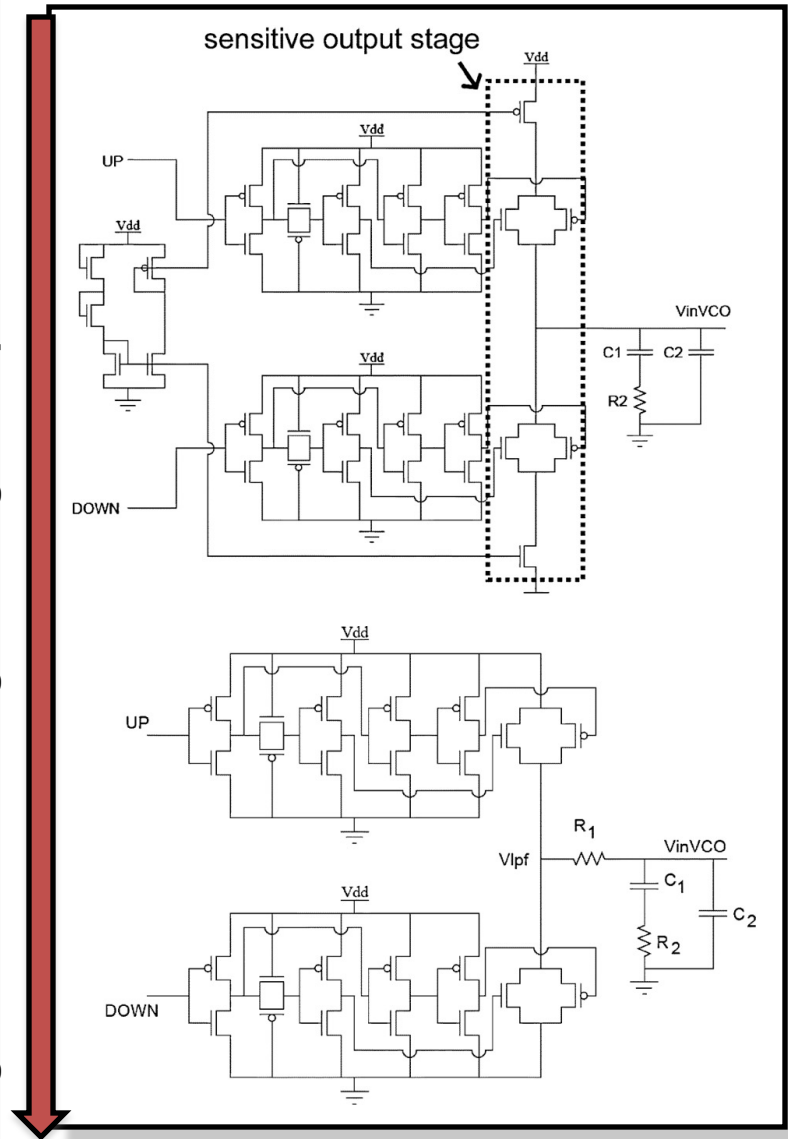
- *high-frequency transients may be filtered by decoupling nodes sensitive to ASETs and introducing a time constant through a series resistor or low-pass filter*

- **Increased Capacitance**

- *increases the amount of charge, Q_{crit} , required to generate an ASET*

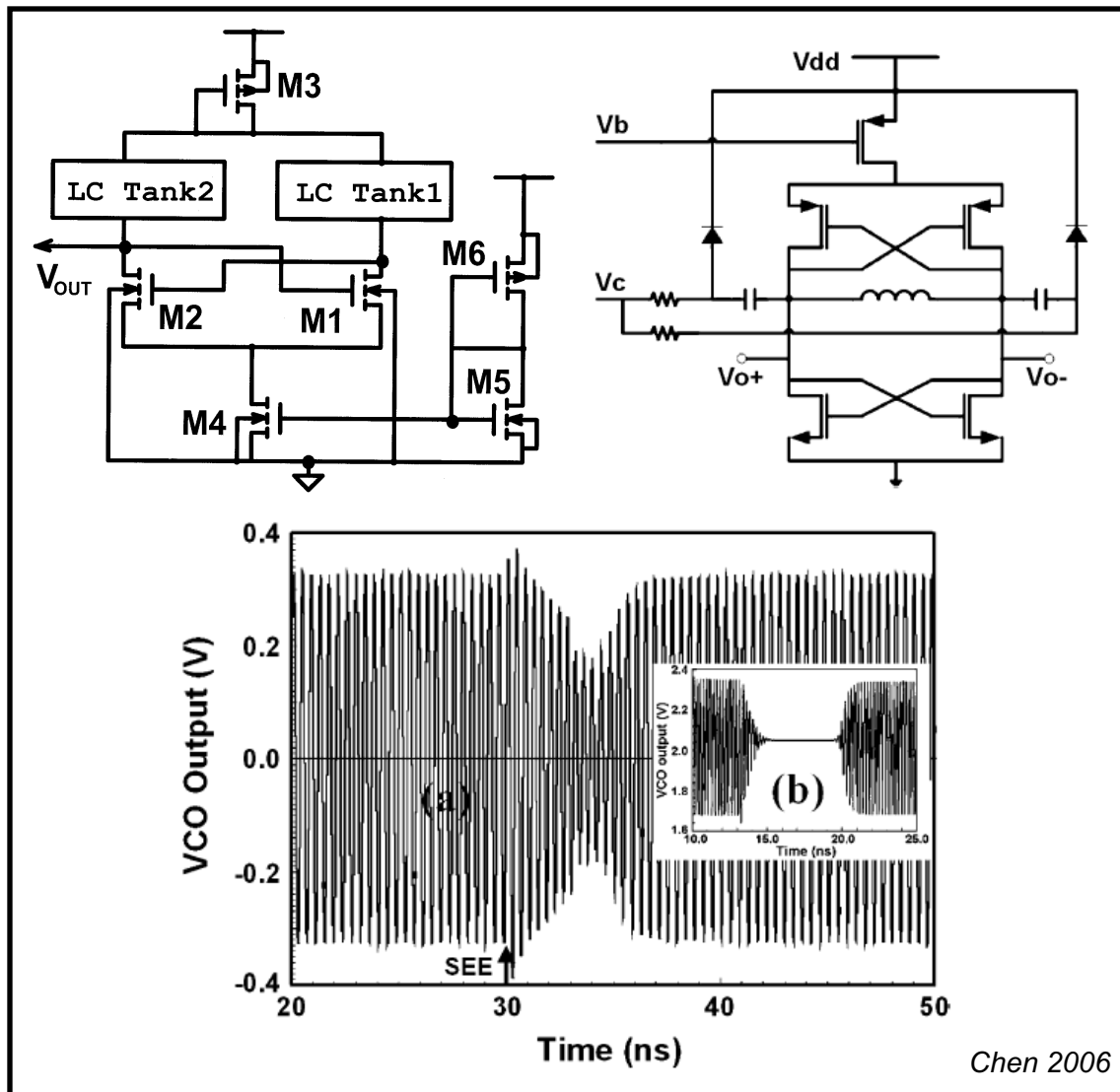
Single-Event Hardening of Charge Pump Sub-Block of PLL

Loveless 2006



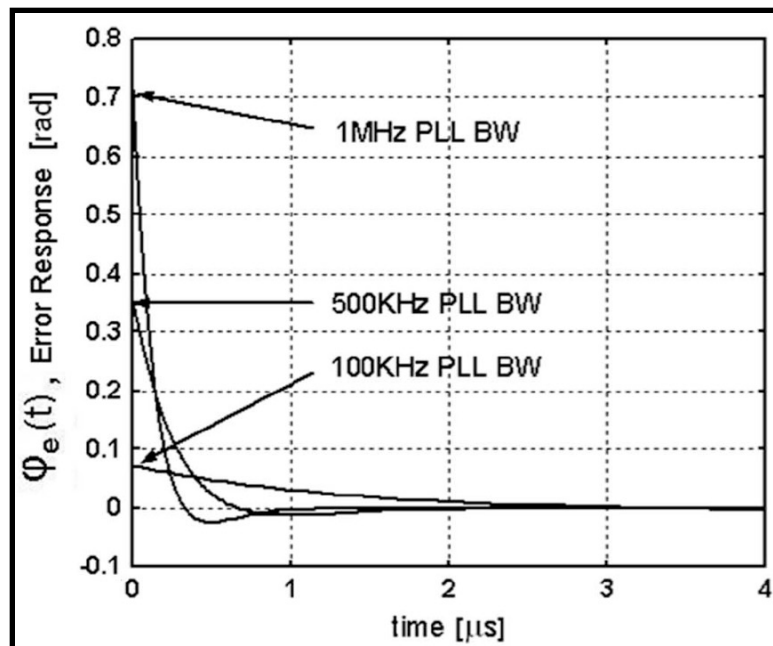
- **Reduction of High Impedance Nodes**
 - *high impedance nodes have consistently been identified as the culprits!*
 - *can be reduced or eliminated at the circuit- or transistor-levels*

Single Event Mitigation By Elimination of High-Impedance Nodes in an LC Tank Oscillator



Chen 2006

- **Modifications in Bandwidth and Gain**
 - *in general, many works on amplifiers, phase-locked loops, voltage-controlled oscillators, ... have shown that **reduction in bandwidth** results in **reduction in SE vulnerability***



Chung 2006

Error Response versus Time During a Single Event in the PLL at Various Bandwidths

Gain-Bandwidth Tradeoffs

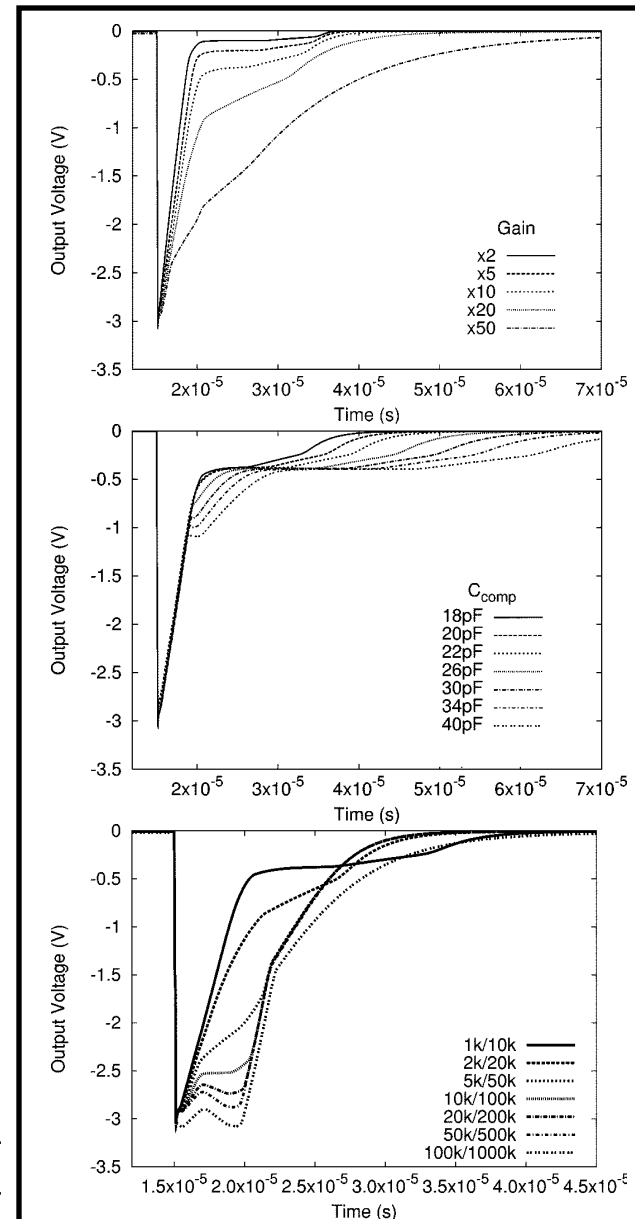


- **Modifications in Bandwidth and Gain**
 - *in general, many works on amplifiers, phase-locked loops, voltage-controlled oscillators, ... have shown that **reduction in bandwidth** results in **reduction in SE vulnerability***
 - *gain and operating speed also play a particular role in determining the SET response*

Ex. “Faster operational amplifier with a smaller gain will have a better SET response than a slower operational amplifier run at a high gain. It also seems to be best to use the smallest practical values to set the closed-loop gain of the amplifier”, Sternberg

SET Dependence on Gain, Capacitance, and Resistance Values in Various Stages in an LM124 Op-Amp

Boulghassoul 2004



- **Modifications in Operating Speed and Current Drive**

- *analog circuits have been shown to exhibit reduced ASET vulnerability for increased operating frequency*



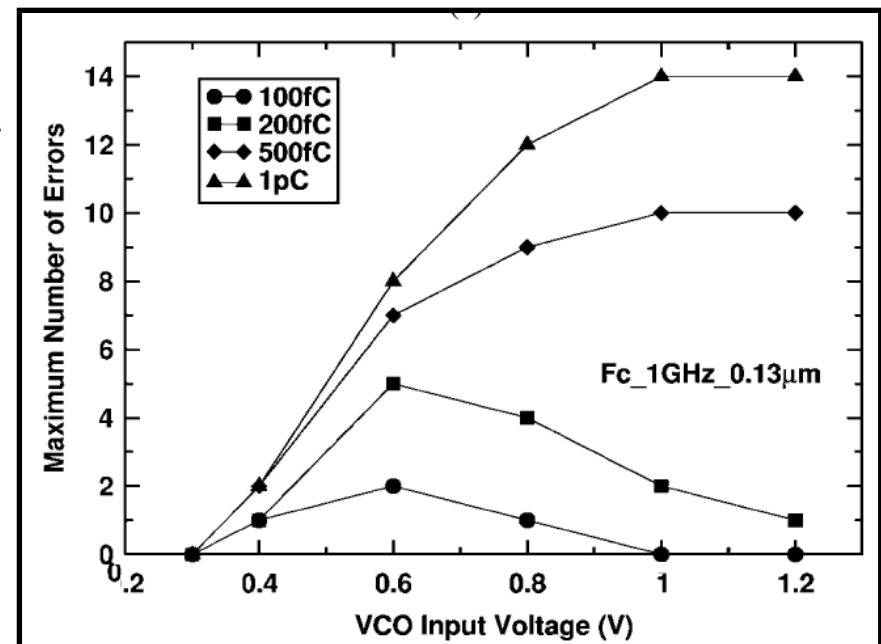
Contrary to that seen in digital circuits

- *increased speed is often accompanied by increased drive current and an improved ability to dissipate the deposited energy, making the circuit less vulnerable*

- **important to attribute the improvement to either speed or drive strength** (*increased bias current is a well-known technique and is often used in AMS circuits for improved SET performance*)

Boulghassoul 2005

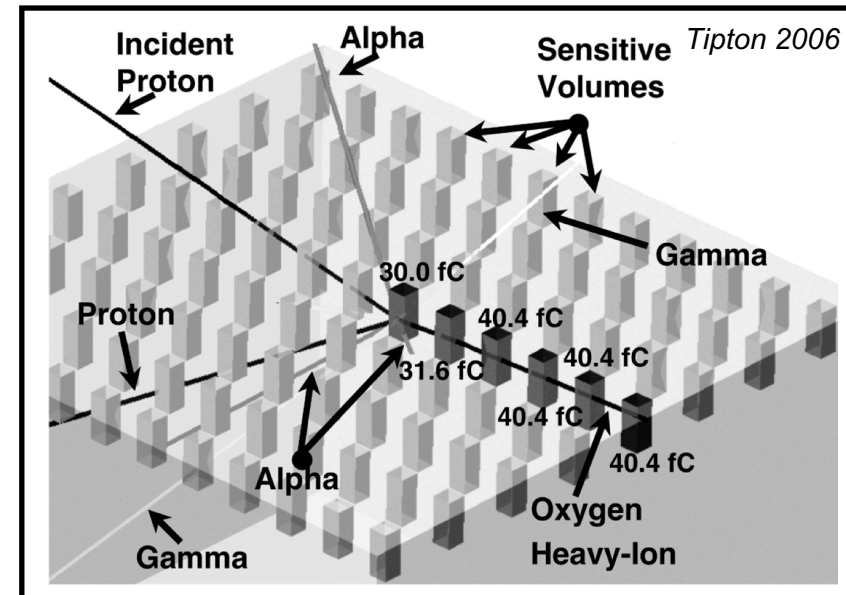
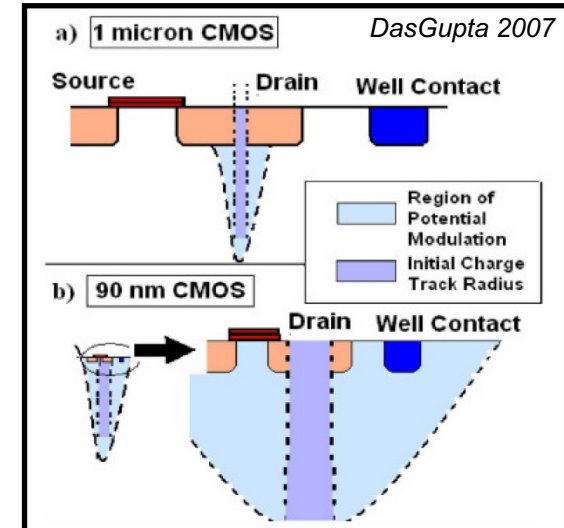
Number of Errors in VCO Output Bits Versus Input Voltage (Proportional to Drive Strength and Frequency)



Circuit Layout-Aware Mitigation



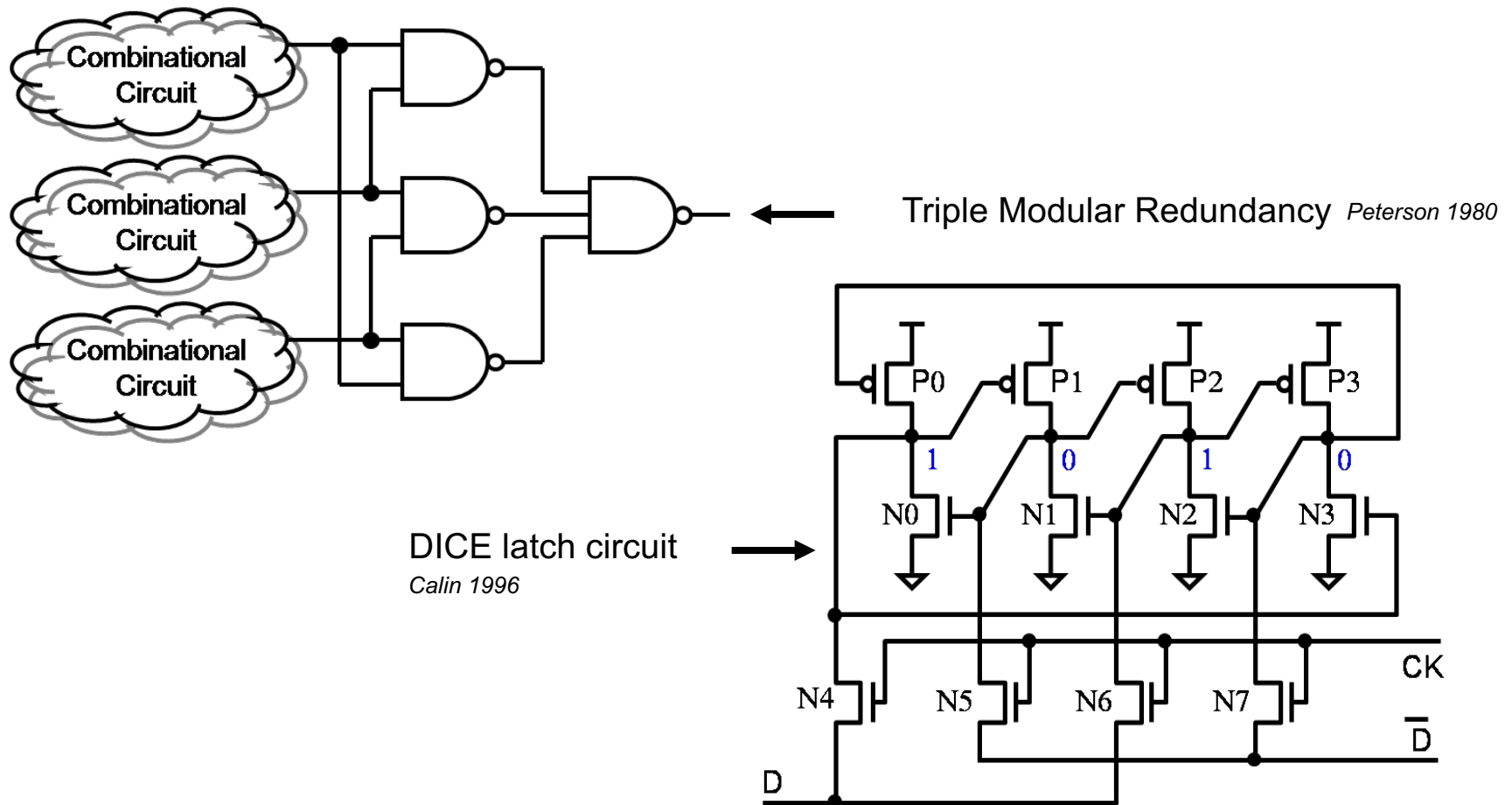
- In recent years, “charge sharing” between transistors has become commonplace:
 - *decreased spacing of devices with technology scaling can increase the charge collection at nodes other than the primary struck node*
 - *layout-level mitigation is becoming increasingly important for ensuring radiation hardness*



Charge Sharing Reliability Issues



Charge sharing can render redundancy-based methods (e.g., Triple Modular Redundancy - TMR and Dual Interlocked Storage Cell - DICE latch) for SEU mitigation less effective



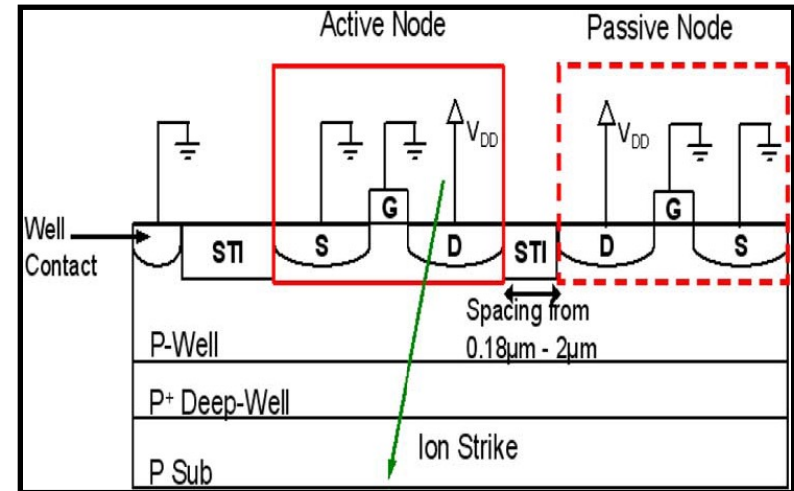
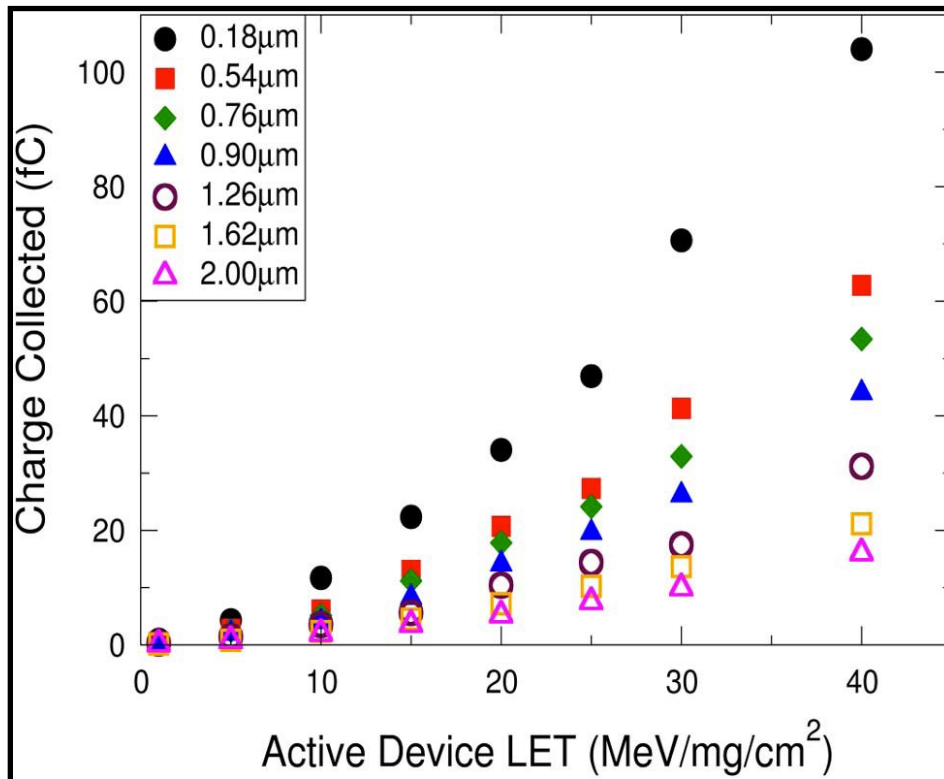
Layout-Level Mitigation: Nodal Separation



Nodal separation:

- increasing the distance between devices can reduce the amount of charge collected on “passive” devices

Amusan 2006



NMOS Cross Section Showing Active (Device Struck by Ionizing Particle) and Passive (Device that Indirectly Collects Charge) Device

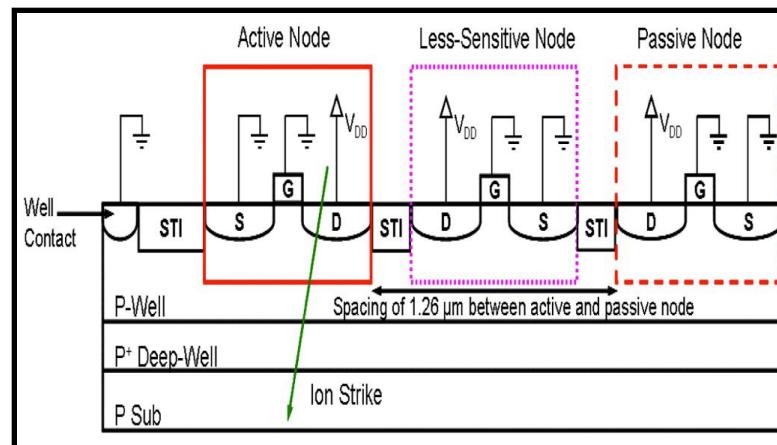
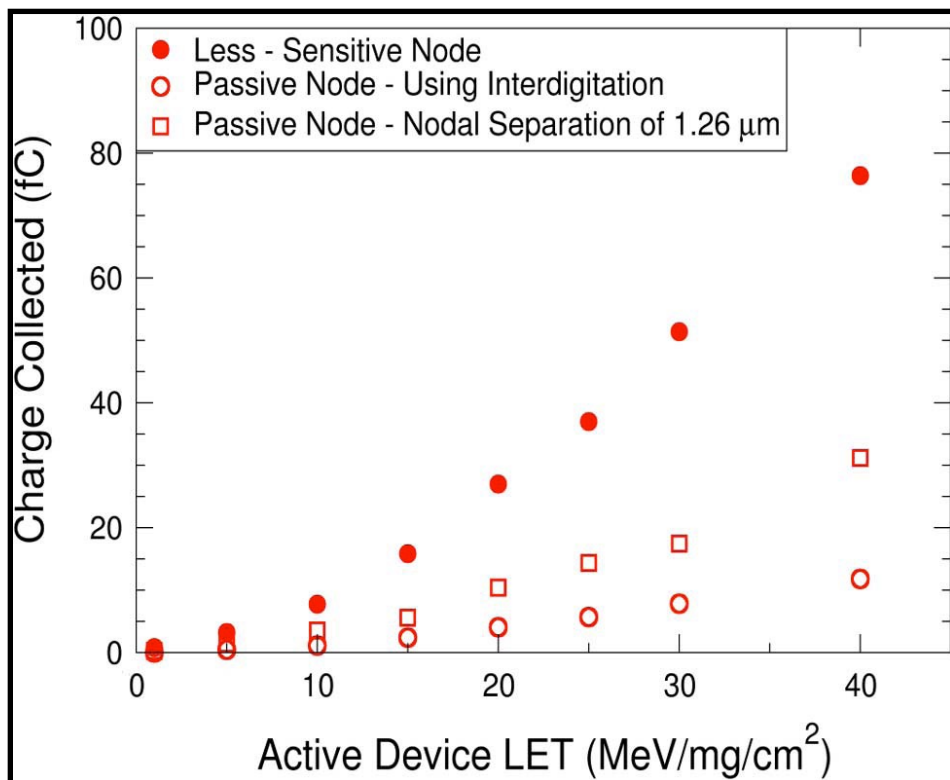
Large Spacing Required To Mitigate Entirely

Nodal Separation of Two PMOS Devices (130 nm CMOS): Charge Collected on Passive Device

Interdigitation (Interleaving):

- “less sensitive” devices placed between critical nodes
- gain benefits of nodal separation without adversely affecting total area

Amusan 2006



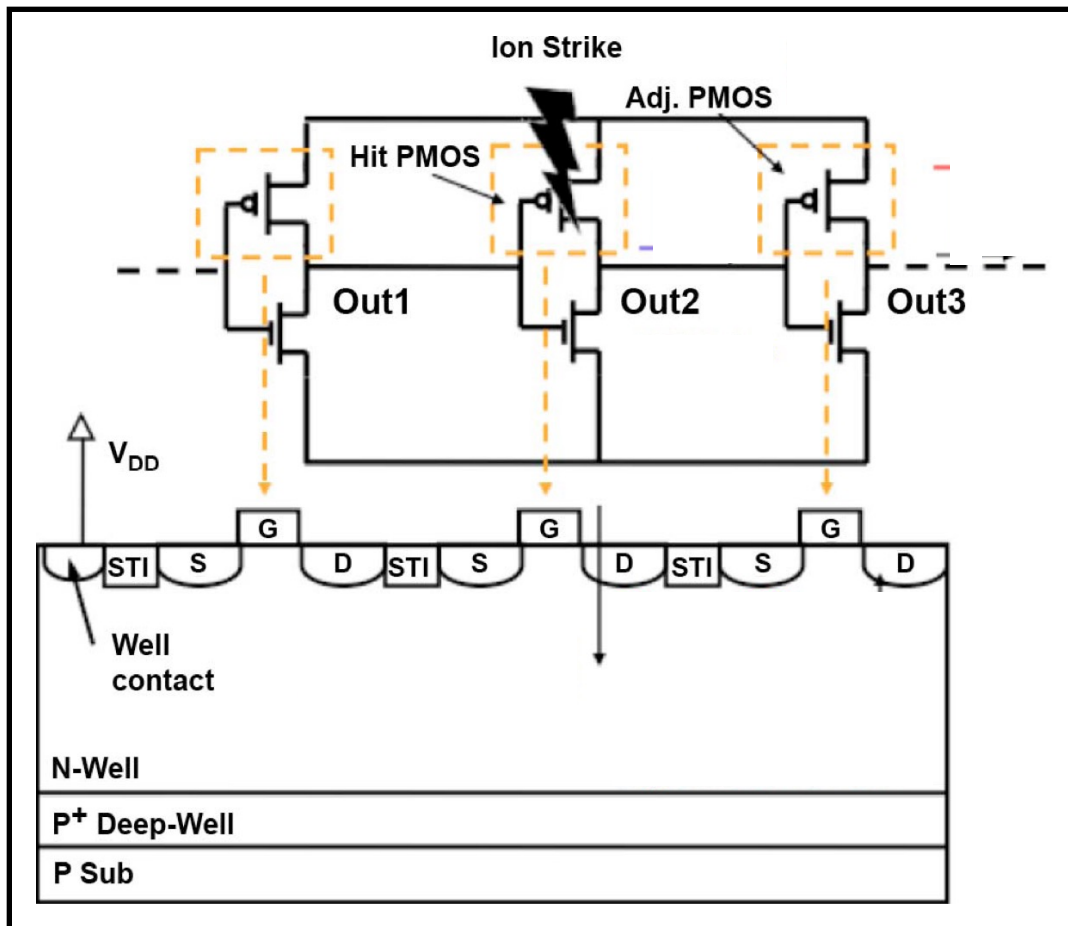
NMOS Cross Section Showing Active and Passive Devices: Less-Sensitive Node is Placed Between Active and Passive Devices

Nodal Separation of Two NMOS Devices (130 nm CMOS): Charge Collected on Passive Device with and without Interdigitation

Instead of Mitigate - Integrate (charge sharing)



The layout orientation and device spacing may be designed so the electrical signal and charge diffusion may interact as to truncate a propagated voltage transient (pulse quenching)



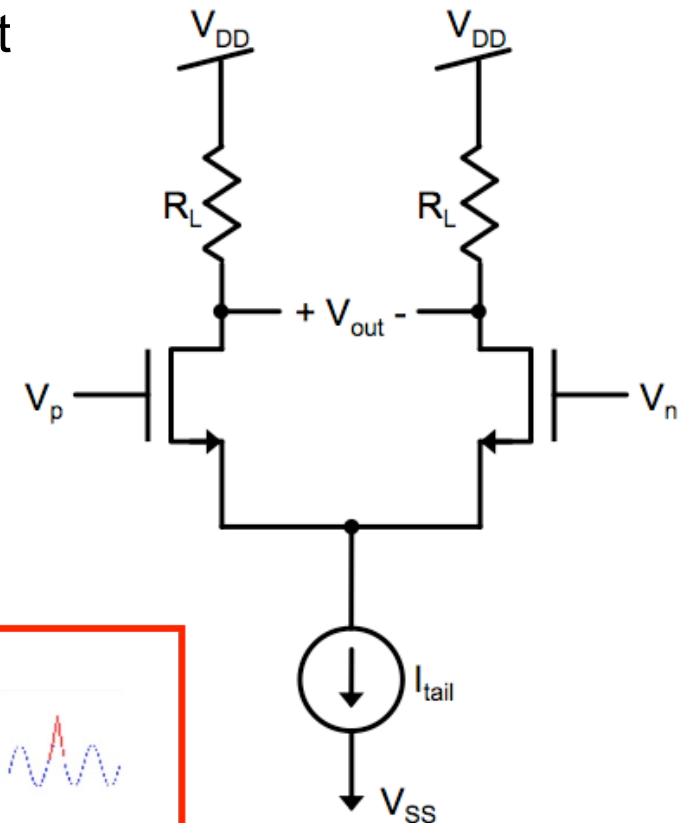
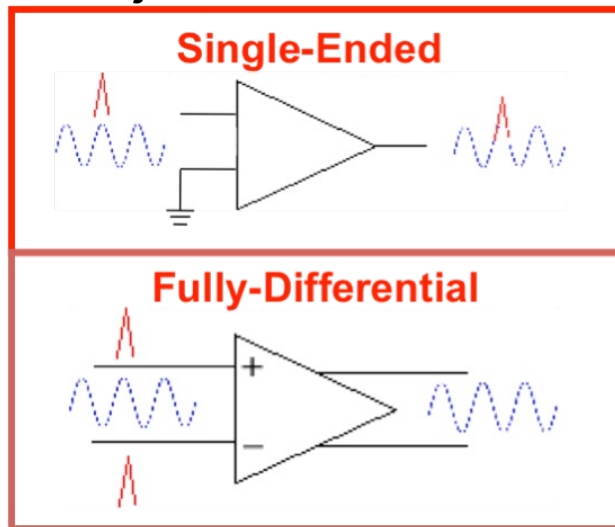
A Similar Mechanism can be Exploited for AMS ASICs

Illustration of Pulse Quenching

Hardening Via Charge Sharing



- Differential topologies are standard in most high-performance analog designs, including amplifiers, data converters, and switched-capacitor circuits
 - *improved dynamic output range and noise rejection over their single-ended counterparts*
 - *highly sensitive to Single-Event Effects!*
- Fully differential topologies reject common-mode noise
 - by maximizing charge sharing such that a single-event transient (SET) is common to both data paths, the SET can be rejected!



Basic Differential Pair

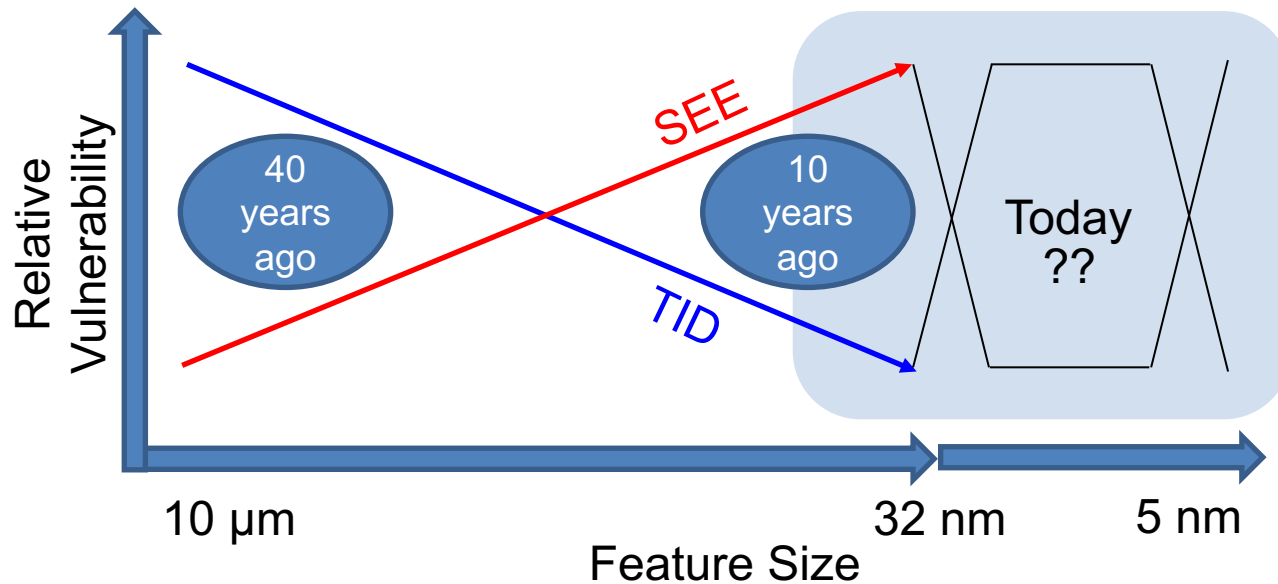


- Radiation Effects in AMS Circuits: Unique issues and considerations
- Total Ionizing Dose and Basic Mitigation Strategies
- Single Event Effects and Basic Mitigation Strategies
- Hardening by Design for AMS
- [A look to the future](#)
- Summary

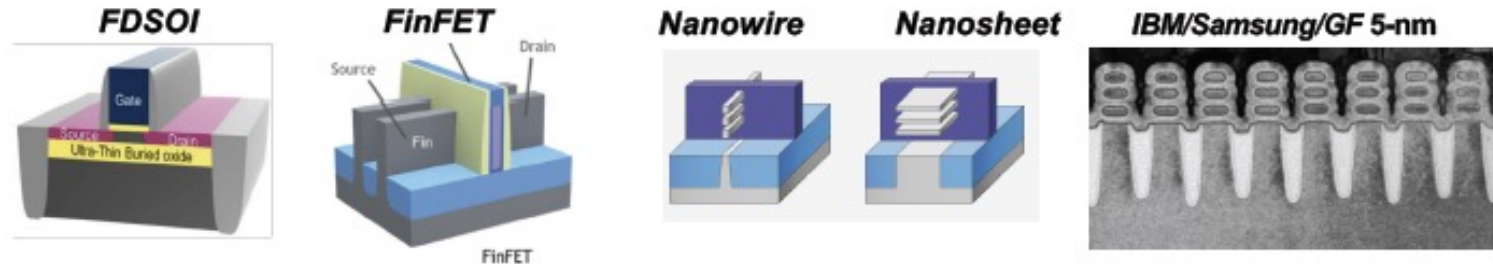
Technology Scaling Trends



- In general, scaling has caused a decrease TID effects, but an increase in SEE
 - *TID improvement: thinner oxides, improved Si-SiO₂ interfaces*
 - *SEE degradation: lower supply voltage, decreased nodal capacitance*



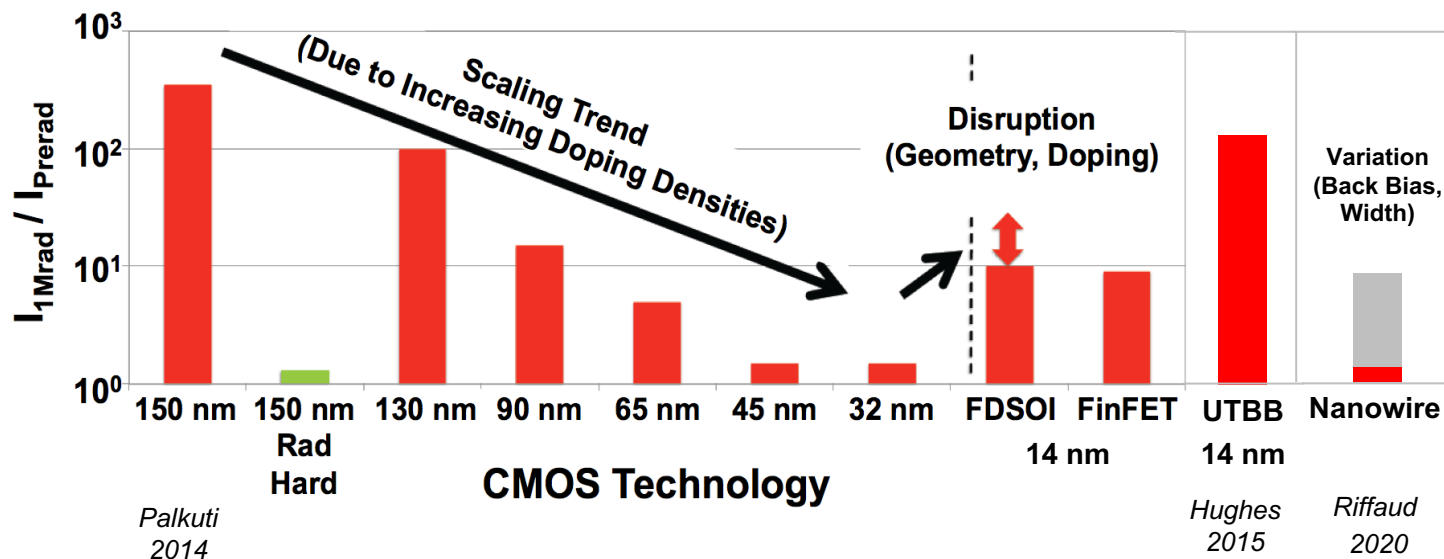
Emerging Technologies: TID



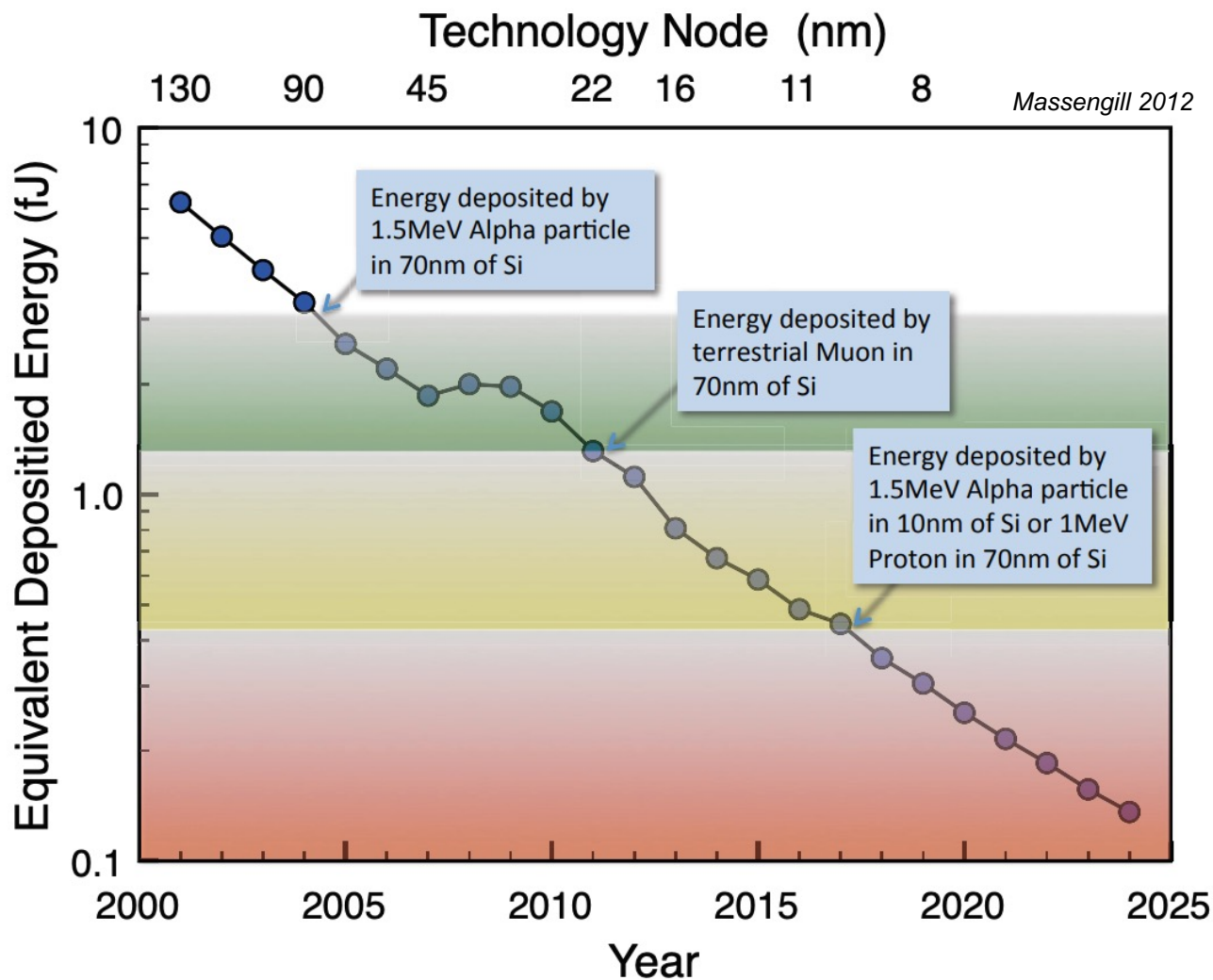
Better electrostatics allows reducing L while controlling SCE

Esqueda, JPL Workshop, 2019

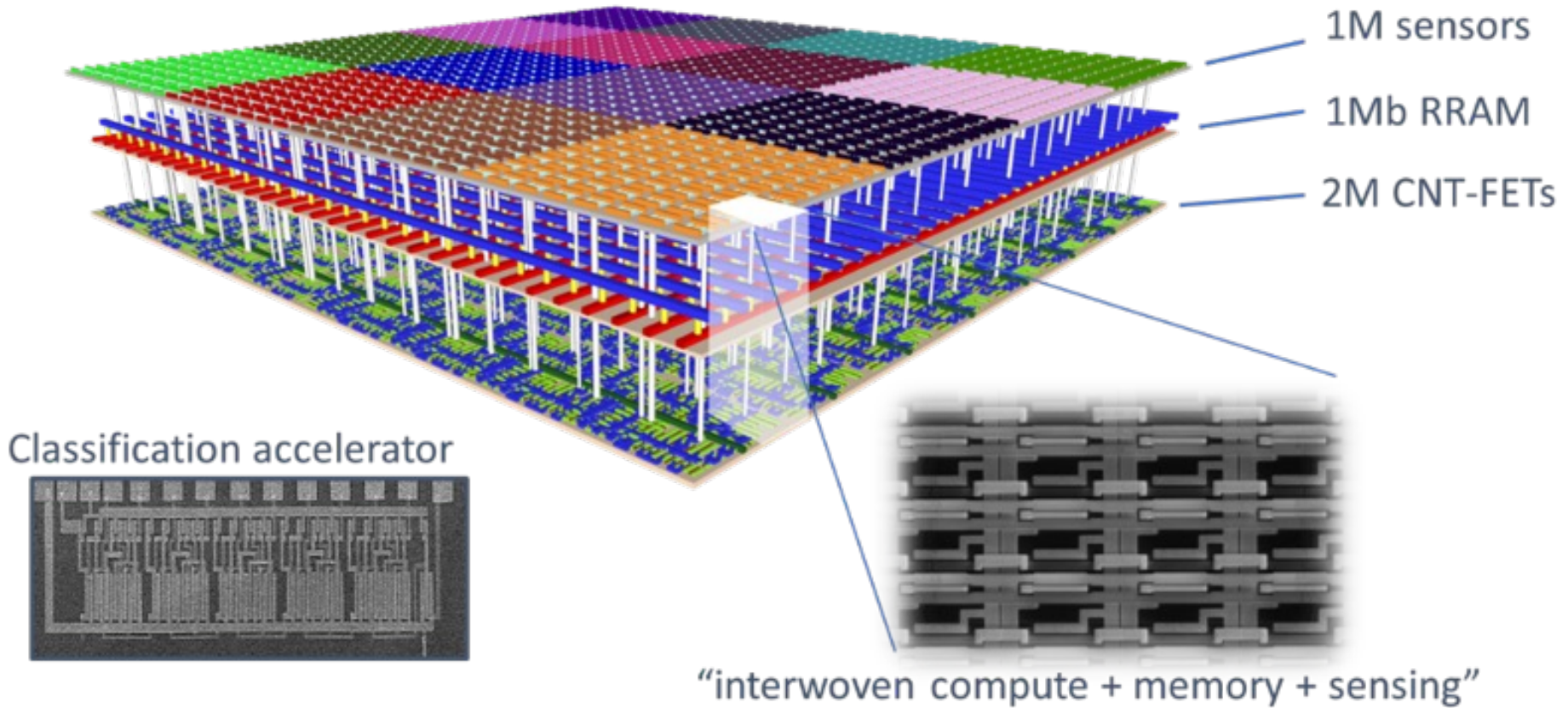
*SCE: Short-Channel Effects



Emerging Technologies: SEE

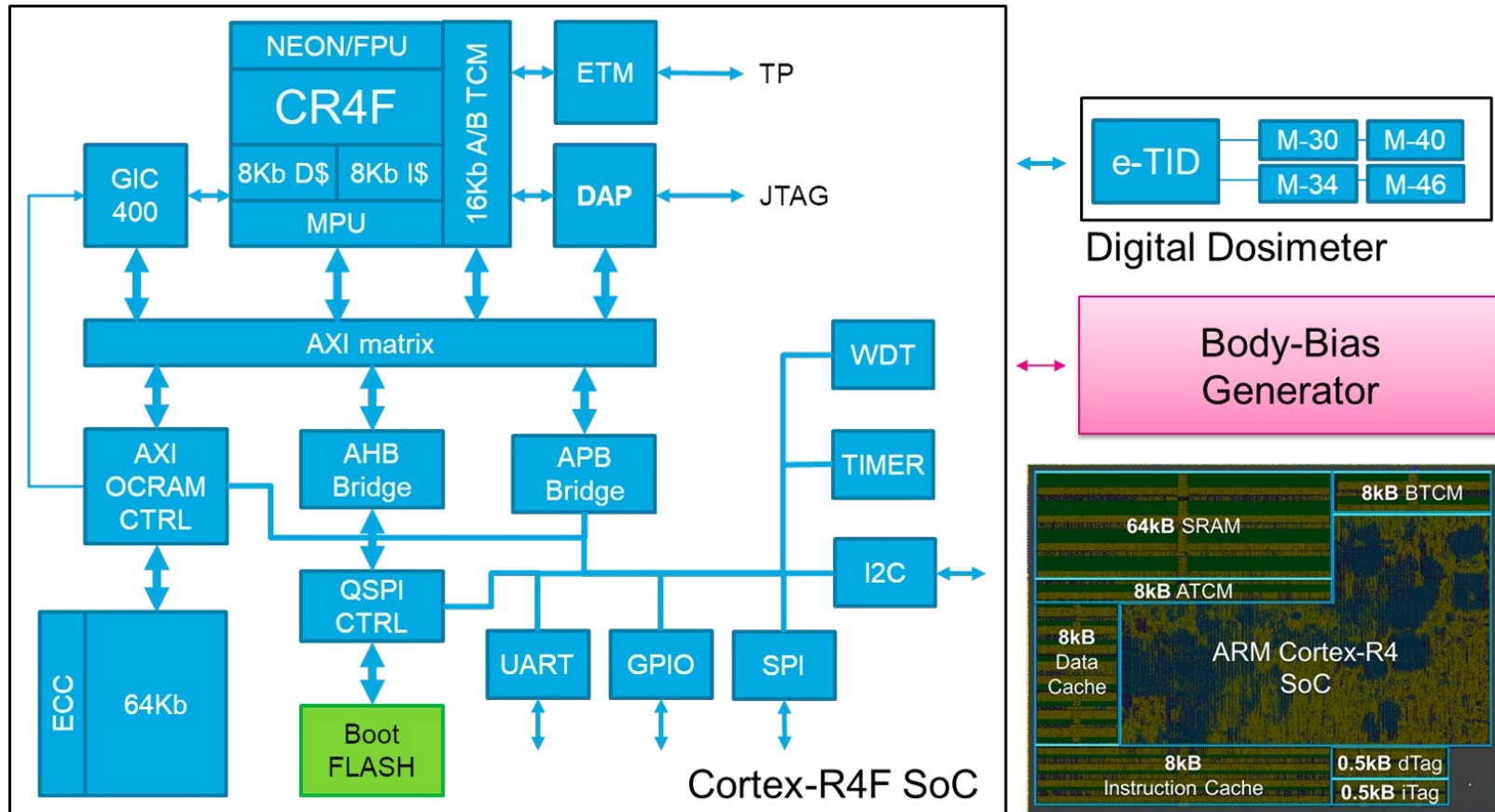


Radiation Hardening by Design



3D-SoC sensor/machine learning IC from Stanford (2017)

Integrated Rad-Hard SoC



Rad-Hard ARM SoC Prototype *Abouzeid 2021*



- Radiation Effects in AMS Circuits
 - *Unique issues and considerations*
 - *Total Ionizing Dose*
 - *Single Event Effects*
- Total Ionizing Dose Mitigation Strategies
- Single Event Effects Mitigation Strategies
- Hardening by Design for AMS
- A look to the future
- Summary

- The ability to put entire systems on a single chip has increased the demand for mixed analog/digital (mixed-signal) circuits
- Total ionizing dose (TID) and single-event (SE) phenomena present challenges for analog & mixed-signal (AMS) systems
 - *TID-induced mismatch can result in a variety of performance penalties and non-monotonic responses*
 - *Single-event transients (SET) are subject to cross-domain response mechanisms*
 - *SE mechanisms may not be tractable using conventional analysis techniques*
 - *New error metrics may be required due to the complexity and functionality*
- However, there is a common thread:
 - *Reduce positive hole trapping or the influence of positive hole trapping in oxides*
 - *Reduce of the sensitivity to TID-induced mismatch*
 - *Reduce collected charge and/or increase critical charge*
 - *SE performance of AMS tends to be dominated by:*
 - gain-bandwidth
 - speed
 - drive strength
 - high-impedance nodes